

STIC Search Report

EIC 1700

STIC Database Tracking Number: 188657

TO: Amanda Walke
Location: REM 9C11
Art Unit : 1752
May 4, 2006

Case Serial Number: 10/800133

From: Usha Shrestha
Location: EIC 1700
REMSSEN 4B28
Phone: 571/272-3519
usha.shrestha@uspto.gov

Search Notes

Examiner Walke,

As per your search request for the Case Number 10/800,133 Claim 17, the applicant's compound is not indexed as the resin structure of Claim 17 in CAS Registry file instead it is indexed as starting compound. So to complete this search I used the Registry Number of starting compound and the Ring Identifier (RID) of acetal resin as of Claim 17. If you have any questions please let me know. Thank you.



STIC Search Results Feedback Form

EIC17000

Questions about the scope or the results of the search? Contact *the EIC searcher* or contact:

Kathleen Fuller, EIC 1700 Team Leader
571/272-2505 REMSEN 4B28

Voluntary Results Feedback Form

- I am an examiner in Workgroup: Example: 1713
- Relevant prior art **found**, search results used as follows:

- ☐ 102 rejection
- ☐ 103 rejection
- ☐ Cited as being of interest.
- ☐ Helped examiner better understand the invention.
- ☐ Helped examiner better understand the state of the art in their technology.

Types of relevant prior art found:

- ☐ Foreign Patent(s)
- ☐ Non-Patent Literature
(journal articles, conference proceedings, new product announcements etc.)

➤ Relevant prior art **not found**:

- ☐ Results verified the lack of relevant prior art (helped determine patentability)
- ☐ Results were not useful in determining patentability or understanding the invention

Comments:

Rush: Cynthia Kelly
SPE Signature

Access DB# 188657

SEARCH REQUEST FORM

Scientific and Technical Information Center

Requester's Full Name: Amanda Wake Examiner #: 75603 Date: 5/4/00
Art Unit: 1752 Phone Number 302-1337 Serial Number: 101800133
Mail Box and Bldg/Room Location: PEM 9C11 Results Format Preferred (circle): PAPER DISK E-MAIL

If more than one search is submitted, please prioritize searches in order of need.

Please provide a detailed statement of the search topic, and describe as specifically as possible the subject matter to be searched. Include the elected species or structures, keywords, synonyms, acronyms, and registry numbers, and combine with the concept or utility of the invention. Define any terms that may have a special meaning. Give examples or relevant citations, authors, etc, if known. Please attach a copy of the cover sheet, pertinent claims, and abstract.

Title of Invention: Bob Sweet Attached

Inventors (please provide full names): _____

Earliest Priority Filing Date: _____

**For Sequence Searches Only* Please include all pertinent information (parent, child, divisional, or issued patent numbers) along with the appropriate serial number.*

Please search for the attached resin as depicted in claim 1 (attached).
~~PLEASE DO NOT SEARCH FOR THE ATTACHED~~
Thank you.

SCIENTIFIC REFERENCE BR
Sci & Tech Inf & Cntr

MAY 4 REC'D

Pat. & T.M. Office

STAFF USE ONLY

Type of Search

Vendors and cost where applicable

10/800133

Classification: 430/270.100

Status: 71 - RESPONSE TO NON-FINAL OFFICE ACTION ENTERED AND FORWARDED TO EXAMINER

Title: DEVELOPMENT ENHANCEMENT OF RADIATION-SENSITIVE ELEMENTS

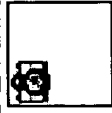
Examiner: WALKER, AMANDA

Inventor: MEMETEA, LIVIA, et al

GAU: 1752

Bib Data report

Application Title: DEVELOPMENT ENHANCEMENT OF RADIATION-SENSITIVE ELEMENTS



Application Num: (in phx) 10/800133 **Filing Date:** 03/12/2004 **Effective Filing:** 03/12/2004
(Location History) (Foreign/Continuity Data)

Status: 71/RESPONSE TO NON-FINAL OFFICE ACTION ENTERED AND FORWARDED TO EXAMINER **Status**
Date: 03/04/2006

Patent Number: Not Issued **Issue Date:** N/A **Date of Abandonment:** N/A
Confirmation Number: 6921 **PALM Location:**

Examiner: 75663 WALKER, AMANDA (Assignment Data) **Group Art Unit:** 1752 **Class/Subclass:**
430/270.100

State or Country: CANADA **Sheets/Drawing:** 0 **Total Claims:** 68 **Independent Claims:** 10

Inventors:

Last name First name: **City:** **Country or State:**

MEMETEA LIVIA

COQUITLAM

CANADA

JARAMILLO JUANA

COQUITLAM

CANADA

BRADFORD NICHOLAS

RICHMOND

CANADA

GAU: 1752

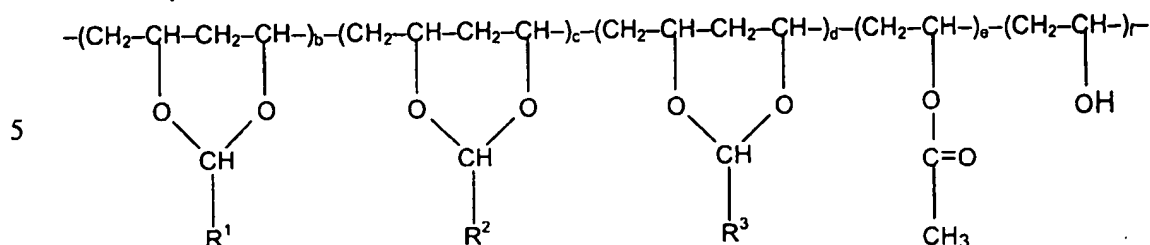
10/800133
Classification: 430/270.100
Status: 71 - RESPONSE TO NON-FINAL OFFICE ACTION ENTERED AND FORWARDED TO EXAMINER
Title: DEVELOPMENT ENHANCEMENT OF RADIATION-SENSITIVE ELEMENTS

Examiner: WALKER, AMANDA
Inventor: MEMETEA, LIVIA, et al

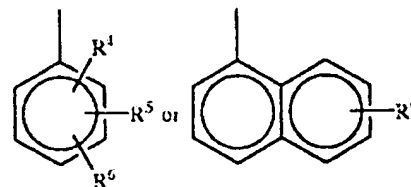
Bib Data report

GOODIN, JONATHAN	TYLER	TEXAS
YANG, CHENG	BURNABY	CANADA
LEVANON, MOSHE	KFAR AHARON	ISRAEL
Attorneys: ALL Attorney Docket No: 91103/JLI		
Interference No: Lost Case: No Unmatched Petition: No L&R Code: 1		

17. The composition of claim 1, wherein the acetal resin has the structure



in which R¹ is --C_nH_{2n+1} where n=1 to 12, and R² is



10 wherein R⁴ = --OH;
R⁵ = --OH or --OCH₃ or Br-- or --O--CH₂--C≡CH and
R⁶ = Br-- or NO₂

R³ = --(CH₂)_t--COOH, --C≡CH, or



15 where R⁷ = COOH, --(CH₂)_t--COOH, --O--(CH₂)_t--COOH

and in which t = 1 to 4, and where b = 5 to 40 mole %, preferably 15 to 35 mole %

c = 10 to 60 mole %, preferably 20 to 40 mole %

d = 0 to 20 mole %, preferably 0 to 10 mole %

e = 2 to 20 mole %, preferably 1 to 10 mole %

20 and f = 5 to 50 mole %, preferably 15 to 40 mole %.

18. A composition according to claim 17, wherein the developability-enhancing compound is at least one of

- 25
- an alcohol having at least one of an alkyl radical of 12 - 60 carbon atoms, a fluoroalkyl radical of 4 - 60 carbon atoms and a fluoroalkylaryl radical of 7 - 60 carbon atoms;
 - a polyol;

=> fil reg

FILE 'REGISTRY' ENTERED AT 14:47:41 ON 04 MAY 2006

=> d his

FILE 'HCAPLUS' ENTERED AT 13:57:15 ON 04 MAY 2006

L1 1 S US20050003296/PN
SEL RN

FILE 'REGISTRY' ENTERED AT 13:57:36 ON 04 MAY 2006

L2 37 S E1-E37
L3 376 S 90-02-8/CRN
L4 25 S 100-83-4/CRN
L5 214 S 123-72-8/CRN
L6 1 S ETHANOL/CN
L7 1 S METHANOL/CN
L8 647 S 9002-89-5/CRN
L9 1 S 90-02-8/RN
L10 1 S 100-83-4/RN
L11 1 S 123-72-8/RN
L12 1 S 9002-89-5/RN
L13 STR
L14 50 S L13
L15 56174 S 46.248/RID
L16 1779 S L15 AND PMS/CI
L17 377 S L3 OR L4 AND L5

FILE 'HCAPLUS' ENTERED AT 14:07:37 ON 04 MAY 2006

L18 93 S L3/DP
L19 1 S L4/DP
L20 8 S L5/DP
L21 93 S L18 OR L19 AND L20
L22 0 S (L18 OR L19) AND L20

FILE 'REGISTRY' ENTERED AT 14:09:03 ON 04 MAY 2006

L23 2 S (L3 OR L4) AND L5

FILE 'HCAPLUS' ENTERED AT 14:09:27 ON 04 MAY 2006

L24 1 S L23
L25 552 S L3
L26 41 S L4
L27 426 S L5
L28 3 S (L25 OR L26) AND L27
L29 11427 S L9
L30 2435 S L10
L31 12010 S L11
L32 410 S (L29 OR L30) AND L31
L33 7 S L32 AND LITHOG?
L34 4 S L32 AND RADIAT?
L35 9 S L33 OR L34
L36 191327 S L6
L37 133365 S L7
L38 217 S L9/DP
L39 18 S L10/DP
L40 111 S L11/DP
L41 5 S (L38 OR L39) AND L40
L42 14 S L24 OR L28 OR L33 OR L34 OR L35 OR L41
L43 1580 S L16
L44 131 S L43 (L) COMPOSITION?
L45 2 S L44 AND LITHOG?

L46 71 S L32 AND (L36 OR L37)
 L47 0 S L46 AND PHOTOG?/SC,SX
 L48 0 S L46 AND PHOTOG?
 L49 13 S L46 AND DEVELOP?
 L50 20 S L44 AND PHOTOG?/SC
 L51 14 S L42 OR L47 OR L48
 L52 20 S L45 OR L50
 L53 20 S L52 NOT L51
 L54 1718 S L8
 L55 62669 S L12
 L56 0 S L54 AND L30
 L57 11 S L55 AND L30
 L58 0 S L57 AND L37
 L59 0 S L57 AND METHANOL
 L60 8 S L57 AND PHOTOG?/SC
 L61 8 S L56 OR L58 OR L59 OR L60
 L62 18 S (L51 OR L61) NOT L53

=> d que 162

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 L4 25 SEA FILE=REGISTRY ABB=ON PLU=ON 100-83-4/CRN
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 L6 1 SEA FILE=REGISTRY ABB=ON PLU=ON ETHANOL/CN
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 L8 647 SEA FILE=REGISTRY ABB=ON PLU=ON 9002-89-5/CRN
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 L16 1779 SEA FILE=REGISTRY ABB=ON PLU=ON L15 AND PMS/CI
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 L26 41 SEA FILE=HCAPLUS ABB=ON PLU=ON L4
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 L38 217 SEA FILE=HCAPLUS ABB=ON PLU=ON L9/DP
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 L41 5 SEA FILE=HCAPLUS ABB=ON PLU=ON (L38 OR L39) AND L40
 L42 14 SEA FILE=HCAPLUS ABB=ON PLU=ON L24 OR L28 OR L33 OR
 L34 OR L35 OR L41
 L43 1580 SEA FILE=HCAPLUS ABB=ON PLU=ON L16
 L44 131 SEA FILE=HCAPLUS ABB=ON PLU=ON L43 (L) COMPOSITION?
 L45 2 SEA FILE=HCAPLUS ABB=ON PLU=ON L44 AND LITHOG?
 L46 71 SEA FILE=HCAPLUS ABB=ON PLU=ON L32 AND (L36 OR L37)
 L47 0 SEA FILE=HCAPLUS ABB=ON PLU=ON L46 AND PHOTOG?/SC,SX
 L48 0 SEA FILE=HCAPLUS ABB=ON PLU=ON L46 AND PHOTOG?

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 L51 14 SEA FILE=HCAPLUS ABB=ON PLU=ON L42 OR L47 OR L48
 L52 20 SEA FILE=HCAPLUS ABB=ON PLU=ON L45 OR L50
 L53 20 SEA FILE=HCAPLUS ABB=ON PLU=ON L52 NOT L51
 L54 1718 SEA FILE=HCAPLUS ABB=ON PLU=ON L8
 L55 62669 SEA FILE=HCAPLUS ABB=ON PLU=ON L12
 L56 0 SEA FILE=HCAPLUS ABB=ON PLU=ON L54 AND L30
 L57 11 SEA FILE=HCAPLUS ABB=ON PLU=ON L55 AND L30
 L58 0 SEA FILE=HCAPLUS ABB=ON PLU=ON L57 AND L37
 L59 0 SEA FILE=HCAPLUS ABB=ON PLU=ON L57 AND METHANOL
 L60 8 SEA FILE=HCAPLUS ABB=ON PLU=ON L57 AND PHOTOG?/SC
 L61 8 SEA FILE=HCAPLUS ABB=ON PLU=ON L56 OR L58 OR L59 OR
 L60
 L62 18 SEA FILE=HCAPLUS ABB=ON PLU=ON (L51 OR L61) NOT L53

=> fil hcap
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=> => d 162 1-18 ibib abs hitstr hitind

L62 ANSWER 1 OF 18 HCAPLUS COPYRIGHT 2006 ACS on STN
 ACCESSION NUMBER: 2006:323592 HCAPLUS
 TITLE: Positive working **lithographic**
 printing plate master showing excellent
 chemical-resistance and developability for
 direct platemaking by IR laser irradiation
 INVENTOR(S): Nakamura, Ippei
 PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 50 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
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JP 2006091781	A2	20060406	JP 2004-280628	

2004
0927

PRIORITY APPLN. INFO.: JP 2004-280628

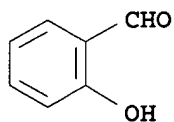
2004
0927

AB The title **lithog.** printing plate master comprises on a
 support a pos.-working recording layer containing an alkali-soluble
 polymer having a sulfonamide group and a vinyl acetal structure.
 The recording layer may include a IR absorbing agent.

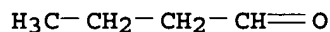
IT 90-02-8D, 2-Hydroxybenzaldehyde, acetals with vinyl
 acetate-vinyl alc. copolymer 123-72-8D, Butyral, acetals
 with vinyl acetate-vinyl alc. copolymer
 (pos. working **lithog.** printing plate master showing
 excellent chemical-resistance and developability for direct
 platemaking by IR laser irradiation)

RN 90-02-8 HCAPLUS

CN Benzaldehyde, 2-hydroxy- (9CI) (CA INDEX NAME)



RN 123-72-8 HCAPLUS
CN Butanal (9CI) (CA INDEX NAME)



CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 38
ST pos working **lithog** printing plate master photoimaging material laser
IT Photoimaging materials
(photopolymerizable; pos. working **lithog**. printing plate master showing excellent chemical-resistance and developability for direct platemaking by IR laser irradiation)
IT **Lithographic** plates
(pos. working **lithog**. printing plate master showing excellent chemical-resistance and developability for direct platemaking by IR laser irradiation)
IT 134127-48-3
(IR dye; pos. working **lithog**. printing plate master showing excellent chemical-resistance and developability for direct platemaking by IR laser irradiation)
IT 63-74-1D, reaction products with vinyl acetate-vinyl alc. copolymer **90-02-8D**, 2-Hydroxybenzaldehyde, acetals with vinyl acetate-vinyl alc. copolymer **123-72-8D**, Butyral, acetals with vinyl acetate-vinyl alc. copolymer 528-44-9D, 1,2,4-Benzenetricarboxylic acid, reaction products with vinyl acetate-vinyl alc. copolymer 25213-24-5D, Vinyl acetate-vinyl alcohol copolymer, acetals, aminosulfonylamides 85622-69-1D, reaction products with vinyl acetate-vinyl alc. copolymer 882045-60-5D, acetals, aminosulfonylamides
(pos. working **lithog**. printing plate master showing excellent chemical-resistance and developability for direct platemaking by IR laser irradiation)

L62 ANSWER 2 OF 18 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 2006:323297 HCAPLUS
TITLE: **Lithographic** printing master plate containing polymer with cyclic structures
INVENTOR(S): Nakamura, Ippei
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 49 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
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JP 2006091772

A2

20060406

JP 2004-280535

2004
0927

PRIORITY APPLN. INFO.:

JP 2004-280535

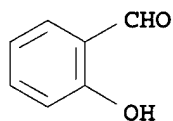
2004
0927

AB Disclosed is a lithog. printing master plate comprising on a support a pos.-working recording layer containing an alkali-soluble polymer having a maleimide-derived cyclic structure and a vinyl acetal-driven cyclic structure.

IT 90-02-8D, 2-Hydroxybenzaldehyde, cyclized polyvinyl acetals; polymers with phenylmaleimide, vinyl acetate, and vinyl alc. 123-72-8D, Butanal, cyclized polyvinyl acetals; polymers with phenylmaleimide, vinyl acetate, and vinyl alc. (Lithog. printing master plate containing polymer with cyclic structures)

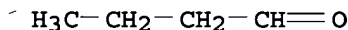
RN 90-02-8 HCAPLUS

CN Benzaldehyde, 2-hydroxy- (9CI) (CA INDEX NAME)



RN 123-72-8 HCAPLUS

CN Butanal (9CI) (CA INDEX NAME)



CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

Section cross-reference(s): 38

ST lithog printing master plate polymer cyclic structure; maleimide vinyl acetal cyclic structure

IT Lithographic plates

(Lithog. printing master plate containing polymer with cyclic structures)

IT Polyvinyl acetals

(Lithog. printing master plate containing polymer with cyclic structures)

IT 90-02-8D, 2-Hydroxybenzaldehyde, cyclized polyvinyl acetals; polymers with phenylmaleimide, vinyl acetate, and vinyl alc. 108-05-4D, Vinyl acetate, polymers with cyclized polyvinyl acetals, phenylmaleimide, and vinyl alc. 123-72-8D, Butanal, cyclized polyvinyl acetals; polymers with phenylmaleimide, vinyl acetate, and vinyl alc. 298-12-4D, cyclized polyvinyl acetals; polymers with phenylmaleimide, vinyl acetate, and vinyl alc. 557-75-5D, Vinyl alcohol, polymers with cyclized polyvinyl acetals, vinyl acetate, and phenylmaleimide 941-69-5D, N-Phenylmaleimide, polymers with cyclized polyvinyl acetals, vinyl acetate, and vinyl alc. 232610-57-0D, polymers with cyclized polyvinyl acetals, phenylmaleimide, vinyl acetate, and vinyl alc. 882045-60-5D, polymers with cyclized polyvinyl acetals, phenylmaleimide, vinyl acetate, and vinyl alc.

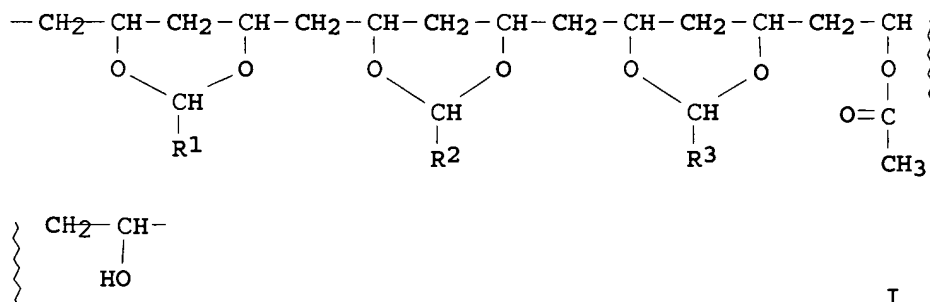
(Lithog. printing master plate containing polymer with

cyclic structures)

L62 ANSWER 3 OF 18 HCAPLUS COPYRIGHT 2006 ACS on STN
 ACCESSION NUMBER: 2005:1050639 HCAPLUS
 DOCUMENT NUMBER: 143:356646
 TITLE: Light-sensitive lithographic
 printing plate
 INVENTOR(S): Nagashima, Akira
 PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
 SOURCE: U.S. Pat. Appl. Publ., 19 pp.
 CODEN: USXXCO
 DOCUMENT TYPE: Patent
 LANGUAGE: English
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 2005214678	A1	20050929	US 2005-89487	2005 0325
JP 2005275231	A2	20051006	JP 2004-91362	2004 0326
PRIORITY APPLN. INFO.:			JP 2004-91362	A 2004 0326

GI



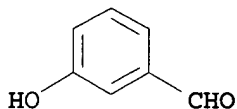
I

AB A light-sensitive lithog. printing plate comprises a hydrophilic substrate provided thereon with an IR light-sensitive layer which comprises an acetal polymer having a specific structure I (R₁ = C1-12 alkyl; R₂ = substituted Ph or substituted 1-naphthyl; and R₃ = carboxyalkyl, ethynyl or substituted phenyl), a polymeric compound carrying, on the side chains, fluorinated aliphatic groups in which the fluorinated aliphatic groups are those derived from fluorinated aliphatic compds. prepared by the telomerization or oligomerization; and a light-heat conversion substance. The light-sensitive lithog. printing plate is excellent in the both printing durability and the developing latitude.

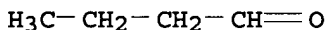
IT 100-83-4D, 3-Hydroxybenzaldehyde, cyclic acetals with polyvinyl alc. 123-72-8D, Butyl aldehyde, cyclic acetals

with polyvinyl alc. **9002-89-5D**, Mowiol 3-98, cyclic acetals with Bu aldehyde and hydroxybenzaldehyde (IR-sensitive **lithog.** printing plate containing polyvinyl acetal)

RN 100-83-4 HCAPLUS
CN Benzaldehyde, 3-hydroxy- (9CI) (CA INDEX NAME)



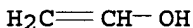
RN 123-72-8 HCAPLUS
CN Butanal (9CI) (CA INDEX NAME)



RN 9002-89-5 HCAPLUS
CN Ethenol, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 557-75-5
CMF C2 H4 O



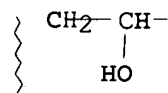
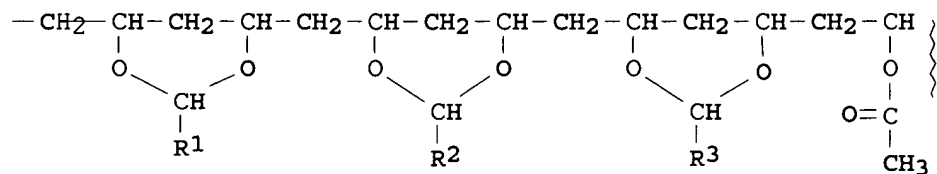
IC ICM G03F007-00
INCL 430270100
CC 74-6 (Radiation Chemistry, Photochemistry, and **Photographic** and Other Reprographic Processes)
ST IR sensitive **lithog** plate polyvinyl acetal fluoropolymer
IT **Lithographic** plates
(IR-sensitive **lithog.** printing plate containing polyvinyl acetal)
IT Fluoropolymers, uses
(IR-sensitive **lithog.** printing plate containing polyvinyl acetal)
IT Anhydrides
Polyvinyl acetals
(cyclic; IR-sensitive **lithog.** printing plate containing polyvinyl acetal)
IT 65-85-0, Benzoic acid, uses 80-09-1, Bis(4-hydroxyphenyl) sulfone 85-42-7, Hexahydrophthalic anhydride 85-43-8, Tetrahydrophthalic anhydride 85-44-9, Phthalic anhydride 89-32-7, Pyromellitic anhydride 96-02-6, Chloromaleic anhydride 100-21-0, Terephthalic acid, uses **100-83-4D**, 3-Hydroxybenzaldehyde, cyclic acetals with polyvinyl alc. 108-30-5, Succinic anhydride, uses 108-31-6, Maleic anhydride, uses 117-08-8, Tetrachlorophthalic anhydride 123-08-0D, 4-Hydroxybenzaldehyde, cyclic acetals with polyvinyl alc. **123-72-8D**, Butyl aldehyde, cyclic acetals with polyvinyl alc. 624-67-9D, Propargyl aldehyde, cyclic acetals with polyvinyl alc. 708-06-5D, 2-Hydroxy-1-naphthaldehyde, cyclic

acetals with polyvinyl alc. 6766-44-5 9002-89-5D,
 Mowiol 3-98, cyclic acetals with Bu aldehyde and
 hydroxybenzaldehyde 36122-35-7, Phenylmaleic anhydride
 117283-53-1 134127-48-3 644965-89-9, Megafac F 780F
 (IR-sensitive lithog. printing plate containing polyvinyl
 acetal)

L62 ANSWER 4 OF 18 HCAPLUS COPYRIGHT 2006 ACS on STN
 ACCESSION NUMBER: 2005:1050638 HCAPLUS
 DOCUMENT NUMBER: 143:356645
 TITLE: Light-sensitive lithographic
 printing plate
 INVENTOR(S): Nagashima, Akira
 PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
 SOURCE: U.S. Pat. Appl. Publ., 14 pp.
 CODEN: USXXCO
 DOCUMENT TYPE: Patent
 LANGUAGE: English
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 2005214677	A1	20050929	US 2005-89480	2005 0325
JP 2005275229	A2	20051006	JP 2004-91360	2004 0326
PRIORITY APPLN. INFO.:			JP 2004-91360	A 2004 0326

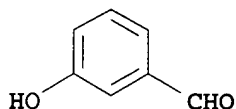
GI



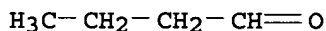
I

AB A light-sensitive lithog. printing plate comprising a hydrophilic substrate provided thereon with a layer sensitive to IR light rays comprising a polymer represented by the following general formula I (R1 = C1-12 alkyl; R2 = substituted Ph or naphthyl; R3 = carboxyalkyl, ethynyl or substituted phenyl); an organic acid and/or a cyclic acid anhydride; and a light-heat conversion substance. The light-sensitive lithog. printing plate is excellent in the both printing durability and the developing latitude.

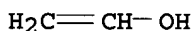
IT 100-83-4D, cyclic acetals with polyvinyl alc.
 123-72-8D, Butanal, cyclic acetals with polyvinyl alc.
 9002-89-5D, Mowiol 3-98, cyclic acetals with Bu aldehyde
 and hydroxybenzaldehyde
 (IR-sensitive lithog. printing plate containing polyvinyl
 acetal)
 RN 100-83-4 HCAPLUS
 CN Benzaldehyde, 3-hydroxy- (9CI) (CA INDEX NAME)



RN 123-72-8 HCAPLUS
 CN Butanal (9CI) (CA INDEX NAME)



RN 9002-89-5 HCAPLUS
 CN Ethenol, homopolymer (9CI) (CA INDEX NAME)
 CM 1
 CRN 557-75-5
 CMF C2 H4 O



IC ICM G03F007-00
 INCL 430270100
 CC 74-6 (Radiation Chemistry, Photochemistry, and
 Photographic and Other Reprographic Processes)
 ST IR sensitive lithog plate polyvinyl acetal
 IT Lithographic plates
 (IR-sensitive lithog. printing plate containing polyvinyl
 acetal)
 IT Anhydrides
 Polyvinyl acetals
 (cyclic; IR-sensitive lithog. printing plate containing
 polyvinyl acetal)
 IT 65-85-0, Benzoic acid, uses 80-09-1, Bis(4-hydroxyphenyl)
 sulfone 85-42-7, Hexahydrophthalic anhydride 85-43-8,
 Tetrahydrophthalic anhydride 85-44-9, Phthalic anhydride
 89-32-7, Pyromellitic anhydride 96-02-6, Chloromaleic anhydride
 100-02-7, p-Nitrophenol, uses 100-21-0, Terephthalic acid, uses
 100-83-4D, cyclic acetals with polyvinyl alc. 104-15-4,
 p-Toluenesulfonic acid, uses 108-30-5, Succinic anhydride, uses
 108-31-6, Maleic anhydride, uses 117-08-8, Tetrachlorophthalic
 anhydride 123-08-0D, cyclic acetals with polyvinyl alc.
 123-72-8D, Butanal, cyclic acetals with polyvinyl alc.
 124-04-9, Adipic acid, uses 624-67-9D, 2-Propynal, cyclic
 acetals with polyvinyl alc. 708-06-5D, 2-Hydroxy-1-
 naphthaldehyde, cyclic acetals with polyvinyl alc. 1571-33-1,

Phenylphosphonic acid 6766-44-5 9002-89-5D, Mowiol
 3-98, cyclic acetals with Bu aldehyde and hydroxybenzaldehyde
 36122-35-7, Phenylmaleic anhydride 117283-53-1 134127-48-3
 (IR-sensitive lithog. printing plate containing polyvinyl
 acetal)

L62 ANSWER 5 OF 18 HCAPLUS COPYRIGHT 2006 ACS on STN

ACCESSION NUMBER: 2005:16956 HCAPLUS

DOCUMENT NUMBER: 142:123213

TITLE: Development enhancement of radiation
 -sensitive elements

INVENTOR(S): Memetea, Livia T.; Jaramillo, Juana G.;
 Bradford, Nicholas; Goodin, Jonathan W.; Yang,
 Cheng; Levanon, Moshe

PATENT ASSIGNEE(S): Can.

SOURCE: U.S. Pat. Appl. Publ., 21 pp., Cont.-in-part
 of U.S. Ser. No. 647,910, abandoned.

CODEN: USXXCO

DOCUMENT TYPE: Patent

LANGUAGE: English

FAMILY ACC. NUM. COUNT: 3

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
-----	----	-----	-----	
US 2005003296	A1	20050106	US 2004-800133	2004 0312
US 2004013965	A1	20040122	US 2003-388488	2003 0317
PRIORITY APPLN. INFO.:			US 2002-364078P	P 2002 0315
			US 2003-388488	A2 2003 0317
			US 2003-647910	B2 2003 0825

OTHER SOURCE(S): MARPAT 142:123213

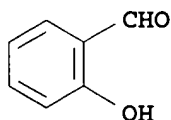
AB A pos.-working radiation-sensitive composition for use with a radiation source comprises one or more polivinyl acetal polymers capable of being dissolved in an alkaline aqueous solution and a development-enhancing compound. The sensitivity of a radiation-sensitive coating based on the composition of this invention is increased without compromising the handling characteristics. Radiation-sensitive elements based on the composition of the invention have good development latitude. A pos.-working lithog. printing precursor is based on the radiation-sensitive composition coated on a hydrophilic surface. The precursor is developable using an alkaline aqueous solution, and may be used with a radiation source in lithog. applications, such as conventional imaging systems, computer-to-plate systems or other direct imaging applications. The precursor is stable in its state before

exposure and has an excellent handling property.

IT 90-02-8DP, 2-Hydroxybenzaldehyde, reaction product with Ethenol homopolymer and butyraldehyde 100-83-4DP, 3-Hydroxybenzaldehyde, reaction product with Ethenol homopolymer and butyraldehyde 123-72-8DP, n-Butyraldehyde, reaction product with Ethenol homopolymer and Hydroxybenzaldehyde 9002-89-5DP, Airvol 103, reaction product with hydroxybenzaldehyde and butyraldehyde (development enhancement of **radiation**-sensitive elements containing)

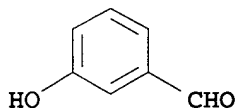
RN 90-02-8 HCAPLUS

CN Benzaldehyde, 2-hydroxy- (9CI) (CA INDEX NAME)



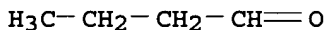
RN 100-83-4 HCAPLUS

CN Benzaldehyde, 3-hydroxy- (9CI) (CA INDEX NAME)



RN 123-72-8 HCAPLUS

CN Butanal (9CI) (CA INDEX NAME)



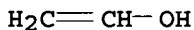
RN 9002-89-5 HCAPLUS

CN Ethenol, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 557-75-5

CMF C2 H4 O



IC ICM G03C001-76

INCL 430270100

CC 74-6 (Radiation Chemistry, Photochemistry, and **Photographic** and Other Reprographic Processes)
Section cross-reference(s): 38

ST development enhancement **radiation** sensitive element

IT **Lithography**
(development enhancement of **radiation**-sensitive elements containing)

IT 90-02-8DP, 2-Hydroxybenzaldehyde, reaction product with Ethenol homopolymer and butyraldehyde 100-83-4DP,

3-Hydroxybenzaldehyde, reaction product with Ethenol homopolymer and butyraldehyde 123-72-8DP, n-Butyraldehyde, reaction product with Ethenol homopolymer and Hydroxybenzaldehyde 9002-89-5DP, Airvol 103, reaction product with hydroxybenzaldehyde and butyraldehyde

(development enhancement of **radiation**-sensitive elements containing)

IT 50-84-0, 2,4-Dichlorobenzoic acid 62-23-7, 4-Nitrobenzoic acid 67-71-0, Dimethylsulfone 87-66-1, 1,2,3-Benzenetriol 89-84-9, 2',4'-Dihydroxyacetophenone 89-86-1, 2,4-Dihydroxybenzoic acid 90-15-3, 1-Naphthol 92-70-6 94-18-8, Benzyl-4-hydroxybenzoate 94-26-8, Butyl-4-hydroxybenzoate 95-14-7, 1H-Benzotriazole 97-29-0, 2,2',4,4'-Tetrahydroxydiphenyl sulfide 99-76-3, Methyl-4-hydroxybenzoate 108-46-3, Resorcinol, uses 118-55-8, Phenyl Salicylate 119-36-8, Methyl salicylate 121-79-9, Propyl gallate 121-92-6, 3-Nitrobenzoic acid 123-31-9, Hydroquinone, uses 131-56-6, 2,4-Dihydroxybenzophenone 136-36-7, Resorcinol monobenzoate 136-77-6, 4-Hexylresorcinol 552-16-9, 2-Nitrobenzoic acid 610-30-0, 2,4-Dinitrobenzoic acid 645-09-0, 3-Nitrobenzamide 1143-72-2, 2,3,4-Trihydroxybenzophenone 1948-33-0, tert-Butyl-hydroquinone 2150-47-2, 2,4-Dihydroxybenzoic acid methyl ester 2283-08-1, 2-Hydroxy-1-naphthoic acid 10288-28-5, 2-(Carbamoylazo)isobutyronitrile 18039-42-4, 5-Phenyl-1H-tetrazole 24207-41-8 62845-75-4
(development enhancement of **radiation**-sensitive elements containing)

L62 ANSWER 6 OF 18 HCAPLUS COPYRIGHT 2006 ACS on STN

ACCESSION NUMBER: 2003:254170 HCAPLUS
DOCUMENT NUMBER: 138:262701
TITLE: Positive acting photoresist composition and imageable element
INVENTOR(S): Levanon, Moshe; Lurie, Emmanuel; Malikov, Sergei; Naigertsik, Oleg; Postel, Larisa
PATENT ASSIGNEE(S): Creo Il. Ltd., Israel
SOURCE: U.S., 15 pp., Cont.-in-part of U.S. 6,255,033.
CODEN: USXXAM
DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 2
PATENT INFORMATION:

PATENT NO. -----	KIND ----	DATE -----	APPLICATION NO. -----	DATE
US 6541181	B1	20030401	US 2000-625582	2000 0726
US 6255033	B1	20010703	US 1999-365279	1999 0730
ES 2218190	T3	20041116	ES 2000-949860	2000 0728
TW 573208	B	20040121	TW 2000-89126927	2000 1215
PRIORITY APPLN. INFO.:			US 1999-365279	A2 1999

0730

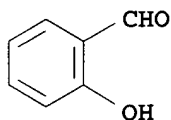
US 2000-625582 A
2000
0726

WO 2000-IB1147 A
2000
0728

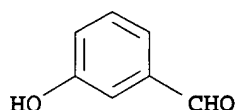
IL 2000-140299 A
2000
1214

IN 2000-KO680 A
2000
1214

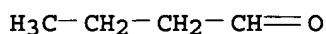
- AB A pos. acting photoresist composition that can be heat-sensitive is presented, either coated on a lithog. base, or on a printing circuit board base, and comprises a water soluble heat-sensitive resin, a novel adhesion promoter and a radiation absorbing agent-a dye or a pigment. An excellent film forming polymer that comprises acetal units directly pendant from the polymer polyvinyl alc. backbone may be the only binder resin, when other resins being optional. The solubility of the coated material in the areas exposed to near -IR laser radiation in mild alkaline developers becomes considerably higher, allowing to obtain high resolved patterns of the etch-resistant material on printing circuit boards or lithog. printing plates. The composition can be applied on the substrate from a liquid of laminated as a dry film. Sensitizers may be added to render the composition sensitive to radiation in a non-thermal sense.
- IT 90-02-8DP, 2-Hydroxybenzaldehyde, cyclic acetals with poly(vinyl alc.) and react product with butyraldehyde
100-83-4DP, 3-Hydroxybenzaldehyde, cyclic acetals with poly(vinyl alc.) and react product with butyraldehyde
123-72-8DP, n-Butyraldehyde, cyclic acetals with poly(vinyl alc.) and react product with hydroxybenzaldehyde and/or glyoxylic acid and/or propargyl aldehyde and/or formylphenoxyacetic acid and/or isovaleraldehyde
(pos. acting photoresist composition and imageable element containing)
- RN 90-02-8 HCAPLUS
- CN Benzaldehyde, 2-hydroxy- (9CI) (CA INDEX NAME)



- RN 100-83-4 HCAPLUS
- CN Benzaldehyde, 3-hydroxy- (9CI) (CA INDEX NAME)



RN 123-72-8 HCAPLUS
CN Butanal (9CI) (CA INDEX NAME)



IC ICM G03C001-77
ICS G03C001-73; G03F007-039; G03F007-09
INCL 430275100; 430277100; 430278100; 430270100; 430905000; 430909000;
430944000; 430326000
CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic and
Other Reprographic Processes)
Section cross-reference(s): 35, 38
IT 90-02-8DP, 2-Hydroxybenzaldehyde, cyclic acetals with
poly(vinyl alc.) and react product with butyraldehyde
100-83-4DP, 3-Hydroxybenzaldehyde, cyclic acetals with
poly(vinyl alc.) and react product with butyraldehyde
121-33-5DP, Vanillin, cyclic acetals with poly(vinyl alc.) and
react product with butyraldehyde and hydroxybenzaldehyde
123-08-0DP, 4-Hydroxybenzaldehyde, cyclic acetals with poly(vinyl
alc.) and react product with butyraldehyde 123-72-8DP,
n-Butyraldehyde, cyclic acetals with poly(vinyl alc.) and react
product with hydroxybenzaldehyde and/or glyoxylic acid and/or
propargyl aldehyde and/or formylphenoxyacetic acid and/or
isovaleraldehyde 298-12-4DP, Glyoxylic acid, cyclic acetals with
poly(vinyl alc.) and react product with butyraldehyde and
hydroxybenzaldehyde 590-86-3DP, Isovaleraldehyde, cyclic acetals
with poly(vinyl alc.) and react product with formylphenoxyacetic
acid and hydroxybenzaldehyde 624-67-9DP, Propargyl aldehyde,
cyclic acetals with poly(vinyl alc.) and react product with
butyraldehyde and hydroxybenzaldehyde 708-06-5DP,
2-Hydroxy-1-naphthaldehyde, cyclic acetals with poly(vinyl alc.)
and react product with butyraldehyde and hydroxybenzaldehyde
2973-77-5DP, 3,5-Dibromo-4-hydroxybenzaldehyde, cyclic acetals
with poly(vinyl alc.) and react product with butyraldehyde
22042-71-3DP, 4-Formylphenoxyacetic acid, cyclic acetals with
poly(vinyl alc.) and react product with isovaleraldehyde and
hydroxybenzaldehyde
(pos. acting photoresist composition and imageable element containing)
REFERENCE COUNT: 30 THERE ARE 30 CITED REFERENCES AVAILABLE
FOR THIS RECORD. ALL CITATIONS AVAILABLE
IN THE RE FORMAT

L62 ANSWER 7 OF 18 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 2001:493021 HCAPLUS
DOCUMENT NUMBER: 136:243278
TITLE: Field evaluation of non-pesticide chemicals as
honey bee repellents
AUTHOR(S): Mayer, D. F.; Lunden, J. D.; Kovacs, G.;
Miliczky, E. R.
CORPORATE SOURCE: Department of Entomology, Irrigated
Agriculture Research & Extension Center,

Washington State University, Prosser, WA,
99350, USA

SOURCE: Colloques - Institut National de la Recherche
Agronomique (2001), 98(Hazards of Pesticides
to Bees), 159-168
CODEN: COLIEZ; ISSN: 0293-1915

PUBLISHER: Institut National de la Recherche Agronomique

DOCUMENT TYPE: Journal

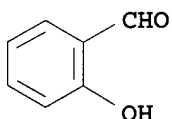
LANGUAGE: English

AB Bee poisoning from pesticides is a serious problem worldwide.
Major concern exists for the safety of honey bees (*Apis mellifera*
L.) as valuable pollinators of many horticultural crops. One way
of reducing the pesticide hazard to bees is to apply a chemical
repellent that will discourage bees from foraging on crops for an
interval after a bee hazard pesticide has been applied. During
1990-1998, the authors conducted field tests on blooming apples
(*Malus domestica* Borkh.), dandelions (*Taraxacum officinale* G.
Weber, in Wiggers), buckwheat (*officinale*) and white Dutch clover
(*officinale*) plants to evaluate their repellent effect to foraging
honey bees. Evaluations were made by slowly walking through the
plots and counting the number of honey bees (30 s/6.7 m/0.91 m swath)
except for apples where they were counted by slowly moving around
and counting the number of honey bees (30 s/1 tree) at 1 and 4 h.
after application. The authors evaluated about 240 non-pesticide
chems. Eleven chems. significantly reduced the number of honey bee
foragers at 1 h. after application but not at 4 h. In some tests,
but not all, 10 chems. significantly reduced the number of honey bee
foragers at 1 h. after application but not at 4 h. One chemical
significantly reduced the number of honey bee foragers at 1 h. and 4
h. after application. In some tests, but not all, 2 chems.
significantly reduced the number of honey bee foragers at 4 h. after
application but not at 1 h.

IT 90-02-8, Salicylaldehyde, biological studies
123-72-8, Butyraldehyde
(field evaluation of non-pesticide chems. as honey bee
repellents)

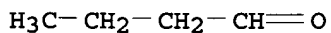
RN 90-02-8 HCAPLUS

CN Benzaldehyde, 2-hydroxy- (9CI) (CA INDEX NAME)



RN 123-72-8 HCAPLUS

CN Butanal (9CI) (CA INDEX NAME)



CC 5-4 (Agrochemical Bioregulators)

IT *Apis mellifera*
Artemisia
Cananga odorata
Cinnamomum zeylanicum
Eucalyptus radiata
Fagopyrum esculentum

Insect repellents

Lavandula

Malus pumila

Mentha piperita

Molasses

Ocimum basilicum

Origanum vulgare

Piper nigrum

Rosmarinus officinalis

Sorghum bicolor

Taraxacum officinale

Thymus (plant)

Trifolium

(field evaluation of non-pesticide chems. as honey bee repellents)

IT 54-12-6, Tryptophan 56-54-2, Quinidine 57-10-3, Palmitic acid, biological studies 57-11-4, Stearic acid, biological studies 60-24-2, 2-Mercaptoethanol 60-35-5, Acetamide, biological studies 64-10-8, Phenylurea 64-19-7, Acetic acid, biological studies 65-30-5 66-25-1, Hexanal 67-63-0, Isopropanol, biological studies 67-66-3, Chloroform, biological studies 67-68-5, Dimethyl sulfoxide, biological studies 71-23-8, Propanol, biological studies 71-36-3, 1-Butanol, biological studies 75-15-0, Carbon disulfide, biological studies 75-50-3, Trimethylamine, biological studies 75-65-0, 2-Methyl-2-propanol, biological studies 76-22-2, Camphor 78-70-6, Linalool 78-93-3, 2-Butanone, biological studies 79-16-3, N-Methylacetamide 79-31-2, Isobutyric acid 79-77-6, β -Ionone 80-59-1, Tiglic acid 83-34-1, Skatole 84-66-2, Diethylphthalate 87-44-5 89-83-8, Thymol 90-02-8, Salicylaldehyde, biological studies 93-58-3, Methyl benzoate 94-96-2 95-48-7, o-Cresol, biological studies 97-53-0, Eugenol 99-03-6, 3'-Aminoacetophenone 99-76-3, p-Hydroxybenzoic acid methyl ester 100-41-4, Ethyl benzene, biological studies 100-52-7, Benzaldehyde, biological studies 101-31-5, 1-Hyoscyamine 103-83-3, Dimethylbenzylamine 104-75-6, 2-Ethylhexylamine 106-35-4, 3-Heptanone 106-44-5, p-Cresol, biological studies 106-65-0, Succinic acid dimethyl ester 106-68-3, 3-Octanone 107-06-2, 1,2-Dichloroethane, biological studies 107-87-9, 2-Pentanone 108-05-4, Vinyl acetate, biological studies 108-31-6, Maleic anhydride, biological studies 108-95-2, Phenol, biological studies 110-12-3, 5-Methyl-2-hexanone 110-13-4, 2,5-Hexanedione 110-43-0, 2-Heptanone 110-54-3, n-Hexane, biological studies 110-93-0, 6-Methyl-5-hepten-2-one 111-13-7, 2-Octanone 111-27-3, 1-Hexanol, biological studies 111-84-2, n-Nonane 111-87-5, 1-Octanol, biological studies 112-14-1, Octylacetate 112-17-4, n-Decylacetate 112-37-8, Undecanoic acid 112-39-0, Palmitic acid methyl ester 112-44-7, Undecanal 119-61-9, Benzophenone, biological studies 120-72-9, Indole, biological studies 122-79-2, Phenyl acetate 123-11-5, p-Anisaldehyde, biological studies 123-19-3, 4-Heptanone 123-72-8, Butyraldehyde 123-92-2, Isoamyl acetate 124-07-2, Caprylic acid, biological studies 125-12-2, Isobornyl acetate 133-06-2, Captan 135-19-3, β -Naphthol, biological studies 136-45-8, MGK repellent 326 138-86-3, Limonene 140-11-4, Benzyl acetate 142-62-1, n-Caproic acid, biological studies 142-82-5, n-Heptane, biological studies 147-85-3, L-Proline, biological studies 147-93-3, o-Mercaptobenzoic acid 328-50-7, α -Ketoglutaric acid 331-39-5, Caffeic acid 334-48-5,

Capric acid 458-37-7, Curcumin 470-82-6, Cineole 471-34-1,
 Calcium carbonate, biological studies 488-10-8, Jasmine
 490-79-9, 2,5-Dihydroxybenzoic acid 499-75-2, Carvacrol
 502-49-8, Cyclooctanone 506-12-7, Heptadecanoic acid 507-70-0,
 Borneol 540-84-1, 2,2,4-Trimethylpentane 544-63-8,
 Tetradecanoic acid, biological studies 546-49-6, Artemisia
 ketone 551-93-9, 2'-Aminoacetophenone 614-18-6, Ethyl
 nicotinate 624-92-0, Methyl disulfide 629-19-6, n-Propyl
 disulfide 638-53-9, Tridecanoic acid 705-86-2,
 8-Decalactone 941-98-0, 1'-Acetonaphthone 1330-43-4,
 Sodium tetraborate 1337-83-3, Aldenal C 11 1596-84-5, Succinic
 acid 2,2-dimethylhydrazide 2016-57-1, Decylamine 2039-88-5,
 2-Bromostyrene 2186-92-7, Anisaldehyde dimethylacetal
 2315-68-6, n-Propyl benzoate 3391-86-4, 1-Octen-3-ol
 3796-70-1, Geranylacetone 4602-84-0, Farnesol 7620-46-4,
 9-Isothiocyanato acridine 7664-38-2, Phosphoric acid, biological
 studies 7704-34-9, Microthiol, biological studies 9004-99-3
 12240-15-2, Prussian Blue 14371-10-9, trans-Cinnamaldehyde
 20244-19-3 23422-53-9, Carzol 92SP 24804-31-7, Calcium oxalate
 hydrate 25414-22-6, 2-Methoxyfuran 27941-88-4, Amino
 acetophenone 36653-82-4, 1-Hexadecanol 41446-60-0,
 cis-7-Tetradecene 62242-52-8, Hexadecanone 70802-40-3
 74214-63-4, β -Carboline-3-carboxylic acid 90823-38-4,
 Ro-Pel 116580-64-4, Margosan O 138261-41-3, NTN 33893-240FS
 143350-75-8, Kinetic 404578-56-9, Algafer LPF 404580-56-9,
 Baitmate 404580-58-1, Can 17 404580-65-0, Compensol
 404580-79-6, N-O-Dor II 404581-66-4, AeroSpray 404582-04-3,
 Epoleon N 100 404582-84-9, Scent-A-Way 404582-85-0, Sun Shield
 404582-89-4, Terramark SPI 404582-90-7, Super Pepper Guard
 404582-91-8, Free Shield 404582-94-1, Frost Shield
 404583-18-2, Fruit Boost (insect attractant) 404583-20-6,
 Nutra-sol 404584-91-4, Get Off My Garden 404585-84-8, Uran 32
 404586-91-0, X-O Deodorizer 404586-92-1, XP 201 404586-93-2,
 Y-Guard 404587-06-0, U-V-Killer

(field evaluation of non-pesticide chems. as honey bee
 repellents)

REFERENCE COUNT: 20 THERE ARE 20 CITED REFERENCES AVAILABLE
 FOR THIS RECORD. ALL CITATIONS AVAILABLE
 IN THE RE FORMAT

L62 ANSWER 8 OF 18 HCAPLUS COPYRIGHT 2006 ACS on STN

ACCESSION NUMBER: 2001:101432 HCAPLUS

DOCUMENT NUMBER: 134:155248

TITLE: Positive acting photoresist composition and
 imaging element

INVENTOR(S): Levanon, Moshe; Lurie, Emmanuel; Malikov,
 Sergei; Postel, Larisa

PATENT ASSIGNEE(S): Creo, Ltd., Israel

SOURCE: PCT Int. Appl., 45 pp.

CODEN: PIXXD2

DOCUMENT TYPE: Patent

LANGUAGE: English

FAMILY ACC. NUM. COUNT: 2

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
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WO 2001009682	A2	20010208	WO 2000-IB1147	2000

0728

WO 2001009682 A3 20010607
 W: AU, CA, JP, MX
 RW: AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU,
 MC, NL, PT, SE

US 6255033 B1 20010703 US 1999-365279

1999

0730

CA 2380570 AA 20010208 CA 2000-2380570

2000

0728

EP 1208014 A2 20020529 EP 2000-949860

2000

0728

EP 1208014 B1 20040414
 R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE,
 MC, PT, IE, FI, CY

AU 762482 B2 20030626 AU 2000-63115

2000

0728

JP 2003530581 T2 20031014 JP 2001-514633

2000

0728

ES 2218190 T3 20041116 ES 2000-949860

2000

0728

TW 573208 B 20040121 TW 2000-89126927

2000

1215

PRIORITY APPLN. INFO.:

US 1999-365279

A

1999

0730

US 2000-625582

A

2000

0726

WO 2000-IB1147

W

2000

0728

IL 2000-140299

A

2000

1214

IN 2000-KO680

A

2000

1214

AB The invention relates to laser direct imaging. A pos. acting, composition that can be heat-sensitive is presented, either coated on a lithog. base, or on a printing circuit board base, and comprises a H2O soluble heat-sensitive resin, a novel adhesion promoter and a radiation absorbing agent - a dye or a pigment. An excellent film forming polymer that comprises acetal units directly pendant from the polymer polyvinyl alc. backbone may be the only binder resin, when other resins being optional. The solubility of the coated material in the areas exposed to near-IR laser radiation in mild alkaline developers becomes considerably higher, allowing to obtain high resolved patterns of the etch-resistant material on printing

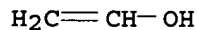
circuit boards or lithog. printing plates. The composition can be applied on the substrate from a liquid or laminated as a dry film. Sensitizers may be added to render the composition sensitive to radiation in a nonthermal sense.

- IT 322413-98-9, Vinyl alcohol-3-hydroxybenzaldehyde-2,6-di-tert-butyl-4-methylphenol copolymer 322414-00-6, Vinyl alcohol-2-hydroxybenzaldehyde-2,6-di-tert-butyl-4-methylphenol-glyoxylic acid copolymer 322414-02-8, Vinyl alcohol-3-hydroxybenzaldehyde-2,6-di-tert-butyl-4-methylphenol-butyraldehyde-propargylaldehyde copolymer 322414-04-0, Vinyl alcohol-2-hydroxybenzaldehyde-2,6-di-tert-butyl-4-methylphenol-3-methoxy-4-hydroxybenzaldehyde-butyraldehyde copolymer 322414-05-1, Vinyl alcohol-4-hydroxybenzaldehyde-2,6-di-tert-butyl-4-methylphenol-2-hydroxy-1-naphthaldehyde-butyraldehyde copolymer 322414-06-2 322414-08-4, Vinyl alcohol-3,5-dibromo-4-hydroxybenzaldehyde-2,6-di-tert-butyl-4-methylphenol-butyraldehyde copolymer
(photoresist composition comprising pos. acting thermal resist layer containing acetal polymer)
- RN 322413-98-9 HCAPLUS
- CN Benzaldehyde, 3-hydroxy-, polymer with 2,6-bis(1,1-dimethylethyl)-4-methylphenol and ethenol (9CI) (CA INDEX NAME)

CM 1

CRN 557-75-5

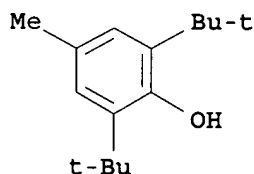
CMF C2 H4 O



CM 2

CRN 128-37-0

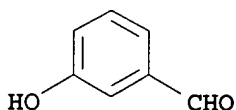
CMF C15 H24 O



CM 3

CRN 100-83-4

CMF C7 H6 O2

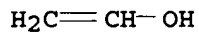


RN 322414-00-6 HCAPLUS
 CN Acetic acid, oxo-, polymer with 2,6-bis(1,1-dimethylethyl)-4-methylphenol, ethenol and 2-hydroxybenzaldehyde (9CI) (CA INDEX NAME)

CM 1

CRN 557-75-5

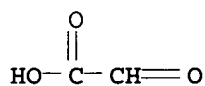
CMF C2 H4 O



CM 2

CRN 298-12-4

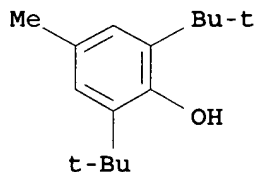
CMF C2 H2 O3



CM 3

CRN 128-37-0

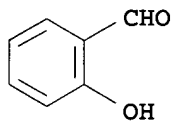
CMF C15 H24 O



CM 4

CRN 90-02-8

CMF C7 H6 O2

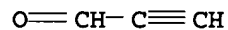


RN 322414-02-8 HCAPLUS
 CN Benzaldehyde, 3-hydroxy-, polymer with 2,6-bis(1,1-dimethylethyl)-4-methylphenol, butanal, ethenol and 2-propynal (9CI) (CA INDEX NAME)

CM 1

CRN 624-67-9

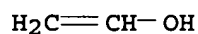
CMF C3 H2 O



CM 2

CRN 557-75-5

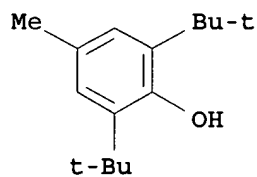
CMF C2 H4 O



CM 3

CRN 128-37-0

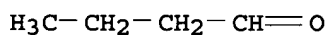
CMF C15 H24 O



CM 4

CRN 123-72-8

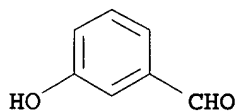
CMF C4 H8 O



CM 5

CRN 100-83-4

CMF C7 H6 O2



RN 322414-04-0 HCAPLUS

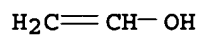
CN Benzaldehyde, 4-hydroxy-3-methoxy-, polymer with
2,6-bis(1,1-dimethylethyl)-4-methylphenol, butanal, ethenol and

2-hydroxybenzaldehyde (9CI) (CA INDEX NAME)

CM 1

CRN 557-75-5

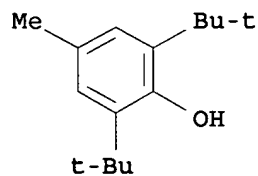
CMF C2 H4 O



CM 2

CRN 128-37-0

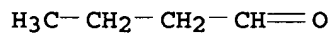
CMF C15 H24 O



CM 3

CRN 123-72-8

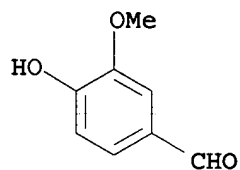
CMF C4 H8 O



CM 4

CRN 121-33-5

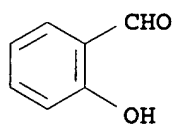
CMF C8 H8 O3



CM 5

CRN 90-02-8

CMF C7 H6 O2



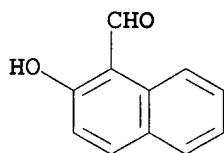
RN 322414-05-1 HCAPLUS

CN 1-Naphthalenecarboxaldehyde, 2-hydroxy-, polymer with
2,6-bis(1,1-dimethylethyl)-4-methylphenol, butanal, ethenol and
4-hydroxybenzaldehyde (9CI) (CA INDEX NAME)

CM 1

CRN 708-06-5

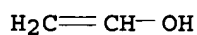
CMF C11 H8 O2



CM 2

CRN 557-75-5

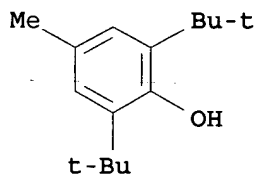
CMF C2 H4 O



CM 3

CRN 128-37-0

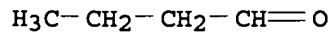
CMF C15 H24 O



CM 4

CRN 123-72-8

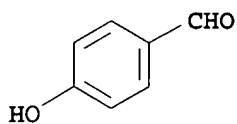
CMF C4 H8 O



CM 5

CRN 123-08-0

CMF C7 H6 O2



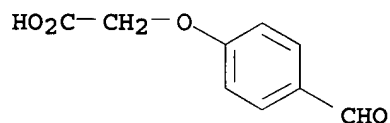
RN 322414-06-2 HCAPLUS

CN Acetic acid, (4-formylphenoxy)-, polymer with 2,6-bis(1,1-dimethylethyl)-4-methylphenol, ethenol, 2-hydroxybenzaldehyde and 3-methylbutanal (9CI) (CA INDEX NAME)

CM 1

CRN 22042-71-3

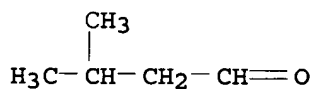
CMF C9 H8 O4



CM 2

CRN 590-86-3

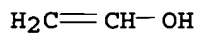
CMF C5 H10 O



CM 3

CRN 557-75-5

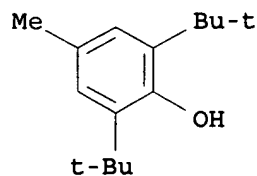
CMF C2 H4 O



CM 4

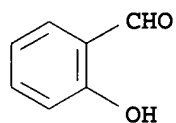
CRN 128-37-0

CMF C15 H24 O



CM 5

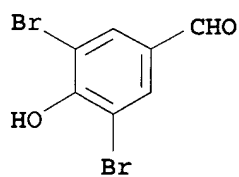
CRN 90-02-8
 CMF C7 H6 O2



RN 322414-08-4 HCAPLUS
 CN Benzaldehyde, 3,5-dibromo-4-hydroxy-, polymer with
 2,6-bis(1,1-dimethylethyl)-4-methylphenol, butanal and ethenol
 (9CI) (CA INDEX NAME)

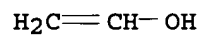
CM 1

CRN 2973-77-5
 CMF C7 H4 Br2 O2



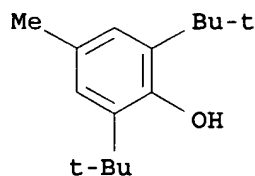
CM 2

CRN 557-75-5
 CMF C2 H4 O



CM 3

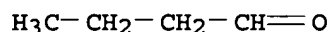
CRN 128-37-0
 CMF C15 H24 O



CM 4

CRN 123-72-8

CMF C4 H8 O



IC ICM G03F007-00

CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

Section cross-reference(s): 76

IT 322413-97-8, Vinyl alcohol-4-hydroxybenzaldehyde-2,6-di-tert-butyl-4-methylphenol copolymer 322413-98-9, Vinyl alcohol-3-hydroxybenzaldehyde-2,6-di-tert-butyl-4-methylphenol copolymer 322414-00-6, Vinyl alcohol-2-hydroxybenzaldehyde-2,6-di-tert-butyl-4-methylphenol-glyoxylic acid copolymer 322414-02-8, Vinyl alcohol-3-hydroxybenzaldehyde-2,6-di-tert-butyl-4-methylphenol-butyraldehyde-propargylaldehyde copolymer 322414-04-0, Vinyl alcohol-2-hydroxybenzaldehyde-2,6-di-tert-butyl-4-methylphenol-3-methoxy-4-hydroxybenzaldehyde-butyraldehyde copolymer 322414-05-1, Vinyl alcohol-4-hydroxybenzaldehyde-2,6-di-tert-butyl-4-methylphenol-2-hydroxy-1-naphthaldehyde-butyraldehyde copolymer 322414-06-2 322414-08-4, Vinyl alcohol-3,5-dibromo-4-hydroxybenzaldehyde-2,6-di-tert-butyl-4-methylphenol-butyraldehyde copolymer (photoresist composition comprising pos. acting thermal resist layer containing acetal polymer)

L62 ANSWER 9 OF 18 HCAPLUS COPYRIGHT 2006 ACS on STN

ACCESSION NUMBER: 2000:861214 HCAPLUS

DOCUMENT NUMBER: 134:49196

TITLE: Laser-sensitive composition for lithographic plate making

INVENTOR(S): Furukawa, Akira; Mitsui, Shinobu

PATENT ASSIGNEE(S): Mitsubishi Paper Mills, Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 15 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2000338669	A2	20001208	JP 1999-131080	1999

PRIORITY APPLN. INFO.:

JP 1999-80653

0512
A
1999
0325

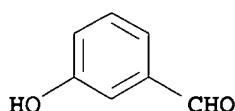
AB The title composition contains an azide and a polymer having oxazoline groups in the side chain. The composition provides a lithog. plate material of the high sensitivity and a lithog. plate of the high printability.

IT 100-83-4D, 3-Hydroxybenzaldehyde, reaction product with polyvinyl alc.

(photoacid generator in laser-sensitive composition)

RN 100-83-4 HCAPLUS

CN Benzaldehyde, 3-hydroxy- (9CI) (CA INDEX NAME)



IT 9002-89-5DP, PVA 105, reaction product with zinc acetate, o-hydroxybenzaldehyde, 4-cyanobenzaldehyde, or 2-aminoethanol

9002-89-5P, PVA 203

(polyvinyl alc. having oxazoline group)

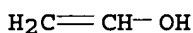
RN 9002-89-5 HCAPLUS

CN Ethenol, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 557-75-5

CMF C2 H4 O



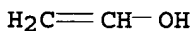
RN 9002-89-5 HCAPLUS

CN Ethenol, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 557-75-5

CMF C2 H4 O



IC ICM G03F007-038

ICS G03F007-00; G03F007-008

CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

IT 100-83-4D, 3-Hydroxybenzaldehyde, reaction product with polyvinyl alc. 42573-57-9 66003-76-7 69432-40-2

(photoacid generator in laser-sensitive composition)

IT 90-02-8DP, o-Hydroxybenzaldehyde, reaction product with modified poly(vinyl alc.) 105-07-7DP, 4-Cyanobenzaldehyde, reaction product with modified poly(vinyl alc.) 141-43-5P,

2-Aminoethanol, preparation 557-34-6DP, Zinc acetate, reaction product with modified poly(vinyl alc.) 9002-89-5DP, PVA 105, reaction product with zinc acetate, o-hydroxybenzaldehyde, 4-cyanobenzaldehyde, or 2-aminoethanol 9002-89-5P, PVA 203 30174-70-0P, Epocros WS 500 259144-30-4P, Epocros K 2010 (polyvinyl alc. having oxazoline group)

L62 ANSWER 10 OF 18 HCAPLUS COPYRIGHT 2006 ACS on STN

ACCESSION NUMBER: 2000:705353 HCAPLUS

DOCUMENT NUMBER: 133:303569

TITLE: Light-sensitive composition for lithographic plate making

INVENTOR(S): Furukawa, Akira; Minato, Ken

PATENT ASSIGNEE(S): Mitsubishi Paper Mills, Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 13 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
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JP 2000275823	A2	20001006	JP 1999-80652	1999 0325

PRIORITY APPLN. INFO.: JP 1999-80652

1999
0325

AB The light-sensitive composition contains polyalkylene oxide, s-triazine substituted with a haloalkyl group or an oxadiazole, and an acid-sensitive crosslinking agent. The composition shows the excellent storage ability and provides a lithog. plate of the excellent printing characteristics.

IT 9002-89-5P, PVA 203
(polyalkylene oxide in light-sensitive material composition)

RN 9002-89-5 HCAPLUS

CN Ethenol, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 557-75-5

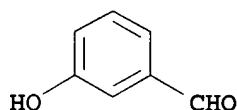
CMF C2 H4 O

H₂C=CH-OH

IT 100-83-4DP, m-Hydroxybenzaldehyde, cyclic polyacetal with poly(vinyl alc.)
(polyalkylene oxide in light-sensitive material composition)

RN 100-83-4 HCAPLUS

CN Benzaldehyde, 3-hydroxy- (9CI) (CA INDEX NAME)



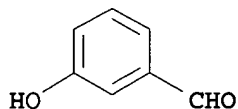
IC 'ICM G03F007-00
ICS G03F007-004; G03F007-038
CC 74-6 (Radiation Chemistry, Photochemistry, and
Photographic and Other Reprographic Processes)
IT 9002-89-5P, PVA 203 127441-50-3DP, cyclic polyacetal
with poly(vinyl alc.)
(polyalkylene oxide in light-sensitive material composition)
IT 57-55-6P, 1,2-Propanediol, preparation 64-19-7DP, Acetic acid,
cyclic polyacetal with poly(vinyl alc.), preparation 90-02-8DP,
o-Hydroxybenzaldehyde, polyvinyl acetal with poly(vinyl alc.)
100-83-4DP, m-Hydroxybenzaldehyde, cyclic polyacetal with
poly(vinyl alc.) 628-89-7DP, reaction products with
poly(4-hydroxystyrene) 24979-70-2DP, reaction products with
2-(2-chloroethoxy)ethanol 312610-28-9DP, cyclic polyacetals with
poly(vinyl alc.)
(polyalkylene oxide in light-sensitive material composition)

L62 ANSWER 11 OF 18 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 2000:705351 HCAPLUS
DOCUMENT NUMBER: 133:303567
TITLE: Light-sensitive lithographic plate
material
INVENTOR(S): Furukawa, Akira
PATENT ASSIGNEE(S): Mitsubishi Paper Mills, Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 9 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2000275821	A2	20001006	JP 1999-80650	1999 0325

PRIORITY APPLN. INFO.: JP 1999-80650
1999
0325

AB The light-sensitive lithog. plate material has a
polyvinyl acetal, an azide, and a near-IR absorbing dye. The
title material provides a lithog. plate of the high
sensitivity and the excellent printing characteristics.
IT 100-83-4DP, m-Hydroxybenzaldehyde, cyclic acetal with
poly(vinyl alc.) 123-72-8DP, Butyral, cyclic acetal with
poly(vinyl alc.) 9002-89-5DP, PVA 203, cyclic acetal
with m-hydroxybenzaldehyde
(polyvinyl acetal in light-sensitive lithog. plate
material)
RN 100-83-4 HCAPLUS
CN Benzaldehyde, 3-hydroxy- (9CI) (CA INDEX NAME)



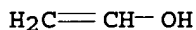
RN 123-72-8 HCAPLUS
 CN Butanal (9CI) (CA INDEX NAME)



RN 9002-89-5 HCAPLUS
 CN Ethenol, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 557-75-5
 CMF C2 H4 O



IC ICM G03F007-00
 ICS G03F007-004; G03F007-008
 CC 74-6 (Radiation Chemistry, Photochemistry, and
Photographic and Other Reprographic Processes)
 ST light sensitive **lithog** plate vinyl benzal polymer
 IT Polyvinyl acetals
 (benzals; light-sensitive **lithog.** plate material)
 IT Light-sensitive materials
Lithographic plates
 (light-sensitive **lithog.** plate material)
 IT Polyvinyl acetals
 (polyvinyl acetal in light-sensitive **lithog.** plate
 material)
 IT 5284-79-7 20237-98-3
 (azide in light-sensitive **lithog.** plate material)
 IT 55281-19-1 134127-48-3
 (near-IR absorbing dye in light-sensitive **lithog.**
 plate material)
 IT 64-19-7DP, Acetic acid, ester with vinyl alc., preparation
100-83-4DP, m-Hydroxybenzaldehyde, cyclic acetal with
 poly(vinyl alc.) **123-72-8DP**, Butyral, cyclic acetal with
 poly(vinyl alc.) **9002-89-5DP**, PVA 203, cyclic acetal
 with m-hydroxybenzaldehyde
 (polyvinyl acetal in light-sensitive **lithog.** plate
 material)

L62 ANSWER 12 OF 18 HCAPLUS COPYRIGHT 2006 ACS on STN
 ACCESSION NUMBER: 1999:219041 HCAPLUS
 DOCUMENT NUMBER: 131:20159
 TITLE: Chitosan staple fibers and their chemical
 modification with some aldehydes
 AUTHOR(S): Hirano, Shigehiro; Nagamura, Kenji; Zhang,
 Min; Kim, Sun Ki; Chung, Byung Geul;

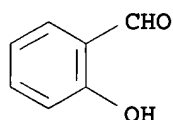
CORPORATE SOURCE: Yoshikawa, Masatoshi; Midorikawa, Takehiko
 SOURCE: Chitin/Chitosan R and D, Tottori, 680, Japan
 Carbohydrate Polymers (1999), 38(4), 293-298
 CODEN: CAPOD8; ISSN: 0144-8617
 PUBLISHER: Elsevier Science Ireland Ltd.
 DOCUMENT TYPE: Journal
 LANGUAGE: English

AB Nine wet-spinning conditions were examined for the preparation of chitosan staple fibers, and 5 novel N-alkylidene and N-arylidene-chitosan staple fibers were obtained by the post-treatment of the chitosan fibers with aldehydes including vanillin. The tenacity and elongation values of the chitosan filaments were almost unchanged by their post-treatment with aldehydes except that with formaldehyde and glyoxal. However, these values decreased significantly in the partially N-modified filaments which were obtained by the pretreatment with vanillin. The chitosan filaments (31-79 μm in diameter) had a scaly structure on the filament surface as examined by SEM observation.

IT 90-02-8DP, 2-Hydroxybenzaldehyde, reaction products with chitosan 123-72-8DP, n-Butyraldehyde, reaction products with chitosan
 (chitosan staple fibers and their chemical modification with some aldehydes)

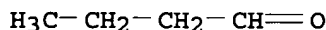
RN 90-02-8 HCAPLUS

CN Benzaldehyde, 2-hydroxy- (9CI) (CA INDEX NAME)



RN 123-72-8 HCAPLUS

CN Butanal (9CI) (CA INDEX NAME)



CC 40-3 (Textiles and Fibers)

IT 50-00-0DP, Formaldehyde, reaction products with chitosan, preparation 90-02-8DP, 2-Hydroxybenzaldehyde, reaction products with chitosan 100-52-7DP, Benzaldehyde, reaction products with chitosan, preparation 107-22-2DP, Glyoxal, reaction products with chitosan 121-33-5DP, Vanillin, reaction products with chitosan 123-38-6DP, Propionaldehyde, reaction products with chitosan 123-72-8DP, n-Butyraldehyde, reaction products with chitosan 9012-76-4DP, Chitosan, reaction products with aldehydes
 (chitosan staple fibers and their chemical modification with some aldehydes)

REFERENCE COUNT: 21 THERE ARE 21 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L62 ANSWER 13 OF 18 HCAPLUS COPYRIGHT 2006 ACS on STN

ACCESSION NUMBER: 1997:618277 HCAPLUS

DOCUMENT NUMBER: 127:301279

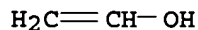
TITLE: A screen printing stencil

INVENTOR(S): Davidson, Robert Stephen; Palmer, Stuart John;
Pratt, Julie E.; Wilson, Stephen Paul
PATENT ASSIGNEE(S): Sericol Ltd., UK; Davidson, Robert Stephen;
Palmer, Stuart John; Pratt, Julie E.; Wilson,
Stephen Paul
SOURCE: PCT Int. Appl., 40 pp.
CODEN: PIXXD2
DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

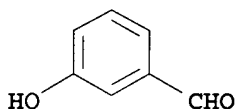
PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
WO 9733202	A1	19970912	WO 1997-GB586	1997 0304
W: AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, CA, CH, CN, CU, CZ, DE, DK, EE, ES, FI, GB, GE, GH, HU, IL, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MD, MG, MK, MN, MW, MX, NO, NZ, PL, PT, RO, RU, SD, SE, SG, SI, SK, TJ, TM, TR, TT, UA, UG, US, UZ, VN, YU, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM RW: GH, KE, LS, MW, SD, SZ, UG, AT, BE, CH, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE, BF, BJ, CF, CG, CI, CM, GA, GN, ML, MR, NE, SN, TD, TG				
AU 9722247	A1	19970922	AU 1997-22247	1997 0304
EP 885408	A1	19981223	EP 1997-905323	1997 0304
EP 885408	B1	20011017		
R: CH, DE, ES, FR, GB, LI				
JP 2000506282	T2	20000523	JP 1997-531557	1997 0304
ES 2166063	T3	20020401	ES 1997-905323	1997 0304
US 5994033	A	19991130	US 1999-142021	1999 0602
PRIORITY APPLN. INFO.:			GB 1996-4578	A 1996 0304
			WO 1997-GB586	W 1997 0304

AB A screen printing stencil is made from a composition comprising polyhydroxy compds. having a plurality of 1,2- or 1,3-diol groups along a polymer backbone, the diol groups grafted thereto a compound of formula $\text{OHCA}[\text{X}[(\text{CH}_2)_m\text{O}]\text{nCOCR}=\text{CH}_2]\text{p}$ (A = an arylene or an alkylene group; X = O, S, a C-C bond, OCH_2CO_2 , CO_2 , NR_1 ; R = H or Me; R_1 = C1-4 alkyl; m is an integer of from 1 to 8; n is an integer of from 1 to 3; and p is 1 or 2) or an acetal of the polyhydroxy compds. with ethylene glycol.

IT 9002-89-5DP, Poly(vinyl alcohol), acetalized
 (preparation and use in photosensitive compns. for manufacture of screen
 printing stencils)
 RN 9002-89-5 HCAPLUS
 CN Ethenol, homopolymer (9CI) (CA INDEX NAME)
 CM 1
 CRN 557-75-5
 CMF C2 H4 O



IT 100-83-4P, 3-Hydroxybenzaldehyde
 (reaction in preparing photosensitive compns. for manufacture of screen
 printing stencils)
 RN 100-83-4 HCAPLUS
 CN Benzaldehyde, 3-hydroxy- (9CI) (CA INDEX NAME)



IC ICM G03F007-12
 ICS G03F007-038; G03F007-021
 CC 74-6 (Radiation Chemistry, Photochemistry, and
 Photographic and Other Reprographic Processes)
 IT 9002-89-5DP, Poly(vinyl alcohol), acetalized
 (preparation and use in photosensitive compns. for manufacture of screen
 printing stencils)
 IT 100-83-4P, 3-Hydroxybenzaldehyde
 (reaction in preparing photosensitive compns. for manufacture of screen
 printing stencils)

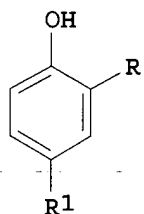
L62 ANSWER 14 OF 18 HCAPLUS COPYRIGHT 2006 ACS on STN

ACCESSION NUMBER: 1996:738154 HCAPLUS
 DOCUMENT NUMBER: 126:20139
 TITLE: Sulfur dyes
 INVENTOR(S): Cote, Philip N.; Domingo, Manuel Jose; Lan,
 Xiangfu; Shakhnovich, Alex I.
 PATENT ASSIGNEE(S): Clariant Finance (Bvi) Limited, Virgin I.
 (Brit.)
 SOURCE: Eur. Pat. Appl., 18 pp.
 CODEN: EPXXDW
 DOCUMENT TYPE: Patent
 LANGUAGE: English
 FAMILY ACC. NUM. COUNT: 2
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
-----	----	-----	-----	
EP 741168	A1	19961106	EP 1996-810271	1996 0429

EP 741168	B1	19990616		
R: BE, CH, DE, ES, FR, GB, IT, LI, PT				
ES 2135198	T3	19991016	ES 1996-810271	1996 0429
JP 08337733	A2	19961224	JP 1996-111743	1996 0502
CN 1143098	A	19970219	CN 1996-110039	1996 0502
BR 9602127	A	19980630	BR 1996-2127	1996 0502
US 5961670	A	19991005	US 1996-741484	1996 1030
HK 1012660	A1	20000505	HK 1998-113846	1998 1217
PRIORITY APPLN. INFO.:			US 1995-434422	A 1995 0503
			US 1996-598759	A 1996 0208
			TR 1996-348	A 1996 0426
			EP 1996-810271	A 1996 0429

OTHER SOURCE(S): MARPAT 126:20139
GI



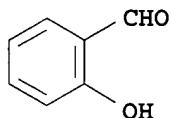
AB Sulfur dyes, with decreased tendering effect on fabrics, are manufactured by reaction of a S compound with phenols I (R, R1 = NO₂, NO, or amino) and reaction of the product with ≥1 of an aldehyde, urea, a benzoquinone or a naphthoquinone, and monoethanolamine or by treating a sulfur dye already prepared from I with ≥1 of an aldehyde, benzoquinone or naphthoquinone, and monoethanolamine. A typical dye was manufactured heating 2,4-dinitrochlorobenzene 100.5, 50% NaOH 87, and water 400 g 1-1.5 h at 100°, slowly mixing the resulting dinitrophenolate

solution with a hot solution prepared from 45% aqueous NaSH.2H₂O 89, S 72, and 50% NaOH 57.2 g at 90-100°, adding 50 g wash water from the phenolate reaction vessel, heating the reaction mixture 30 min at 104-106° while collecting 200 mL water; adding 700 g water, cooling to 35°, adding 28 g 40% glyoxal solution, heating the mixture 12 h at 122°, oxidizing the resulting solution 2 h at 65° by bubbling in O, adjusting the pH to 7.5, filtering, solubilizing the presscake (74 g) with 50% NaOH 30, 45% aqueous NaSH.2H₂O 23.3, and water 89 g at 85°, and heating 2 h at 105°.

IT 90-02-8DP, reaction products with desulfurized C.I. Sulfur Black 1 123-72-8DP, Butanal, reaction products with desulfurized C.I. Sulfur Black 1
(modified sulfur dyes for decreased tendering of fabrics)

RN 90-02-8 HCAPLUS

CN Benzaldehyde, 2-hydroxy- (9CI) (CA INDEX NAME)



RN 123-72-8 HCAPLUS

CN Butanal (9CI) (CA INDEX NAME)



IC ICM C09B049-00

CC 41-8 (Dyes, Organic Pigments, Fluorescent Brighteners, and Photographic Sensitizers)
Section cross-reference(s): 40

IT 50-00-0DP, Formaldehyde, reaction products with desulfurized C.I. Sulfur Black 1, preparation 57-13-6DP, Urea, reaction products with desulfurized C.I. Sulfur Black 1, preparation 90-02-8DP, reaction products with desulfurized C.I. Sulfur Black 1 106-51-4DP, 2,5-Cyclohexadiene-1,4-dione, reaction products with desulfurized C.I. Sulfur Black 1, preparation 107-20-0DP, reaction products with desulfurized C.I. Sulfur Black 1 107-22-2DP, Glyoxal, reaction products with desulfurized C.I. Sulfur Black 1 111-30-8DP, Pentanedial, reaction products with desulfurized C.I. Sulfur Black 1 117-80-6DP, 2,3-Dichloro-1,4-naphthoquinone, reaction products with desulfurized C.I. Sulfur Black 1 118-75-2DP, 2,3,5,6-Tetrachloro-1,4-benzoquinone, reaction products with desulfurized C.I. Sulfur Black 1 123-72-8DP, Butanal, reaction products with desulfurized C.I. Sulfur Black 1 141-43-5DP, reaction products with C.I. Sulfur Black 1 298-12-4DP, reaction products with C.I. Sulfur Black 1 623-27-8DP, 1,4-Benzenedicarboxaldehyde, reaction products with desulfurized C.I. Sulfur Black 1 1326-82-5DP, C.I. Sulphur Black 1, desulfurized, derivs.
(modified sulfur dyes for decreased tendering of fabrics)

L62 ANSWER 15 OF 18 HCAPLUS COPYRIGHT 2006 ACS on STN

ACCESSION NUMBER: 1991:515801 HCAPLUS

DOCUMENT NUMBER: 115:115801

TITLE: Epoxy resin compositions for sealing semiconductor devices
 INVENTOR(S): Imura, Tetsuro; Ota, Masayuki; Fukuzawa, Takao
 PATENT ASSIGNEE(S): Yuka Shell Epoxy K. K., Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 9 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
-----	----	-----	-----	
JP 03074426	A2	19910329	JP 1989-210106	1989 0816

PRIORITY APPLN. INFO.: JP 1989-210106
 1989
 0816

AB The title compns., giving cured products with good heat, moisture, and crack resistance, comprise epoxy resin hardeners, inorg. fillers, and epoxy resins with hydrolyzable halo content <1000 ppm, prepared from (2-methyl)epihalohydrin and novolak resins of reaction products of a (1 or 2 C1-9 alkyl or aryl-substituted) hydroquinone and an aldehyde or ketone selected from R1COR1, R2CO(CH2)mCOR2, R2CH:CHCOR2, R2COC6H3(OH)R3, and benzenedialdehyde [each R1 = H, C1-5 alkyl, (halo-substituted)Ph; each R2 = H, C1-5 alkyl, Ph; R3 = H, C1-5 alkyl, methoxy]. Thus, epichlorohydrin-treated formaldehyde-methylhydroquinone copolymer (I) 100.0, Epikote 5050 10.0, novolak phenol resin 79.8, RD-8 551.0, and additives 14 parts were blended, crushed, transfer molded, and cured 5 h at 170° to give samples having glass temperature 215°, crack resistance (cracked after 100 cycles of 5 min each at -50° and +200°) 0/20, and moisture resistance (50% failure in 120° vapor and 15 V bias voltage) 310 h, vs. 165, 5/20, and 210, resp., for samples containing Epikote 180S65 instead of I.

IT 135899-26-2D, reaction products with epichlorohydrin
 135942-51-7

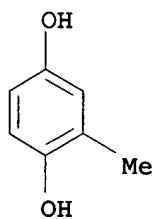
(potting compns. containing, for semiconductors)

RN 135899-26-2 HCAPLUS

CN Benzaldehyde, 2-hydroxy-, polymer with 2-methyl-1,4-benzenediol (9CI) (CA INDEX NAME)

CM 1

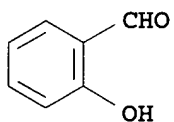
CRN 95-71-6
 CMF C7 H8 O2



CM 2

CRN 90-02-8

CMF C7 H6 O2



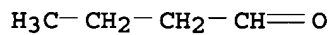
RN 135942-51-7 HCAPLUS

CN Butanal, polymer with formaldehyde and 1-(4-hydroxyphenyl)ethanone
(9CI) (CA INDEX NAME)

CM 1

CRN 123-72-8

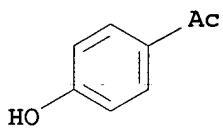
CMF C4 H8 O



CM 2

CRN 99-93-4

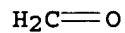
CMF C8 H8 O2



CM 3

CRN 50-00-0

CMF C H2 O



IC ICM C08G059-08
 ICS C08G059-20; H01L023-29; H01L023-31
 CC 37-6 (Plastics Manufacture and Processing)
 Section cross-reference(s): 76
 IT 106-89-8D, reaction products with novolak resins 117674-30-3D,
 reaction products with epichlorohydrin 135899-24-0D, reaction
 products with epichlorohydrin 135899-25-1D, reaction products
 with epichlorohydrin 135899-26-2D, reaction products
 with epichlorohydrin 135899-27-3D, reaction products with
 epichlorohydrin 135942-51-7
 (potting compns. containing, for semiconductors)

L62 ANSWER 16 OF 18 HCAPLUS COPYRIGHT 2006 ACS on STN

ACCESSION NUMBER: 1987:642675 HCAPLUS

DOCUMENT NUMBER: 107:242675

TITLE: Glutaraldehyde-aldehyde disinfecting and
 sterilizing compositions, particularly
 effective against tuberculosis bacteria
 INVENTOR(S): Ascenzi, Joseph Michael; Gordon, Michael
 David; Bruckner, Norman Irving

PATENT ASSIGNEE(S): Surgikos, Inc., USA

SOURCE: Eur. Pat. Appl., 25 pp.

CODEN: EPXXDW

DOCUMENT TYPE: Patent
 LANGUAGE: English

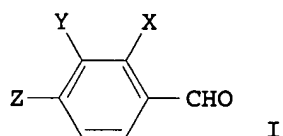
FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO. -----	KIND ----	DATE -----	APPLICATION NO. -----	DATE
EP 232996	A1	19870819	EP 1987-300538	1987 0122
EP 232996 R: AT, BE, CH, DE, ES, FR, GB, IT, LI, LU, NL, SE IN 164910	B1 A	19900103 19890701	IN 1986-CA953	1986 1229
AU 8767878	A1	19870730	AU 1987-67878	1987 0121
AU 586064 CA 1314207	B2 A1	19890629 19930309	CA 1987-527854	1987 0121
DK 8700363	A	19870724	DK 1987-363	1987 0122
JP 62201801	A2	19870905	JP 1987-11462	1987 0122
JP 07094361 BR 8700284	B4 A	19951011 19871208	BR 1987-284	1987 0122
ZA 8700479	A	19880831	ZA 1987-479	1987 0122

AT 49101	E	19900115	AT 1987-300538	1987 0122
ES 2121730	T3	19981216	ES 1987-300538	1987 0122
PRIORITY APPLN. INFO.:			US 1986-821660	A 1986 0123
			EP 1987-300538	A 1987 0122

GI



AB Sterilizing and disinfecting solns., which are particularly effective against Mycobacterium tuberculosis and related species at 20°, contain 0.3-6 weight% glutaraldehyde and 0.01-0.6 weight% of a conjugated monoaldehyde selected from a) α,β -unsatd. C6-10 aldehydes R1CR2:CR3CHO (R1 = H, C1-3 hydrocarbyl, Ph; R2, R3 = H, Me), b) PhCHO, and c) substituted benzaldehydes I (X, Y = H, OH, halo; Z = H, OH, Me, OMe, halo, nitro; YZ = OCH2O; OH groups are not on adjacent C atoms). The addition of a number of α,β -unsatd. monoaldehydes to a 2% aqueous glutaraldehyde solution showed enhanced tuberculocidal activity. The glutaraldehyde solution alone showed 4.6 + 104 organisms (M. bovis BCG test organism)/4.40 + 105 initial organisms after 10 min and 2.4 + 103 after 30 min, at 20°. However, addition of 0.33 weight% 2-hexenal gave 0 organisms/4.5 + 105 initial organisms after 10 min., and 0.11 weight% PhCH:CMcCHO also gave 0/6.8 + 105 initial organisms after 10 min., at 20°.

IT 111645-71-7 111645-78-4 111645-79-5
(disinfection and sterilization with, against tuberculosis bacteria)

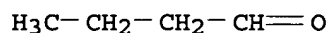
RN 111645-71-7 HCAPLUS

CN Pentanedial, mixt. with butanal (9CI) (CA INDEX NAME)

CM 1

CRN 123-72-8

CMF C4 H8 O



CM 2

CRN 111-30-8

CMF C5 H8 O2

OHC-(CH₂)₃-CHO

RN 111645-78-4 HCAPLUS

CN Pentanedial, mixt. with 2-hydroxybenzaldehyde (9CI) (CA INDEX NAME)

CM 1

CRN 111-30-8

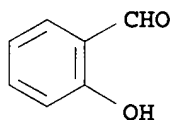
CMF C5 H8 O2

OHC-(CH₂)₃-CHO

CM 2

CRN 90-02-8

CMF C7 H6 O2



RN 111645-79-5 HCAPLUS

CN Pentanedial, mixt. with 3-hydroxybenzaldehyde (9CI) (CA INDEX NAME)

CM 1

CRN 111-30-8

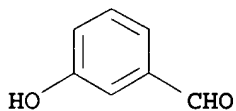
CMF C5 H8 O2

OHC-(CH₂)₃-CHO

CM 2

CRN 100-83-4

CMF C7 H6 O2



IC ICM A01N035-02

ICS A01N035-04

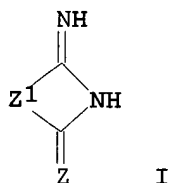
ICI A01N035-02; A01N035-04, A01N035-02
 CC 63-8 (Pharmaceuticals)
 IT 80411-13-8 111645-64-8 111645-65-9 111645-66-0 111645-67-1
 111645-68-2 111645-69-3 111645-70-6 111645-71-7
 111645-72-8 111645-73-9 111645-74-0 111645-75-1
 111645-76-2 111645-77-3 111645-78-4
 111645-79-5 111645-80-8 111645-81-9 111645-82-0
 111645-83-1 111645-85-3, Glutaraldehyde-vanillin mixture
 111645-86-4, Glutaraldehyde-isovanillin mixture 111645-87-5,
 Glutaraldehyde-veratraldehyde mixture 111713-87-2
 (disinfection and sterilization with, against tuberculosis
 bacteria)

L62 ANSWER 17 OF 18 HCAPLUS COPYRIGHT 2006 ACS on STN
 ACCESSION NUMBER: 1985:229534 HCAPLUS
 DOCUMENT NUMBER: 102:229534
 TITLE: Color imaging method and material
 PATENT ASSIGNEE(S): Asahi Chemical Industry Co., Ltd., Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 9 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 59227485	A2	19841220	JP 1983-102830	1983 0610
JP 04016354	B4	19920323	JP 1983-102830	1983 0610

PRIORITY APPLN. INFO.:

GI



AB A color imaging method consists of contacting with heating,
 ≥ 1 compound selected from aromatic aldehydes and
 paraformaldehyde with ≥ 1 compound having the general formula
 I (Z = NH, (OR)₂; R = lower alkyl; Z1 = aromatic or heterocyclic
 group that can form a conjugated system with C:NH group). The
 claim includes fixing procedure by which the imino group in I is
 inactivated and also the imaging material that contains ≥ 1
 of the claimed 2 components in the receptor. The method and the
 material provide color images resistant to light and chems. Thus,
 2 dispersions were prepared which resp. contained (A)
 1,3-diimino-4,5,6,7-tetrachloroisindoline 1, 5% aqueous poly(vinyl

alc.) 2, and H₂O 2 parts, and added with 20% poly(vinyl alc.) 3 parts, and (B) 1,4-diformylbenzene 1, 5% poly(vinyl alc.) 2, and H₂O 2 parts, and added with 20% poly(vinyl alc.) 3 parts. The 2 dispersions were mixed (1:1) and the mixture was coated on a plain paper sheet (3 g/m²). Application. of 140° heat with pressure produced blue-green coloration, which was unaffected by contact with dioctyl phthalate droplets for 1 wk. Exposure to sunlight for 15 days had no effect. Treating the colored material with a 10% solution of xylylene diisocyanate in PhMe fixed the image and reheating did not produce further coloration.

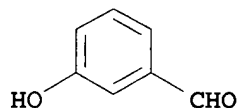
IT 9002-89-5
(color-forming compns. containing aromatic aldehyde, imino compound and, for thermal recording materials)
RN 9002-89-5 HCAPLUS
CN Ethenol, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 557-75-5
CMF C2 H4 O

H₂C=CH-OH

IT 100-83-4
(color-forming compns. containing imino compound and, for thermal recording materials)
RN 100-83-4 HCAPLUS
CN Benzaldehyde, 3-hydroxy- (9CI) (CA INDEX NAME)



IC ICM B41M005-18
ICS D06P001-42
CC 74-12 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
IT 557-05-1 9002-89-5
(color-forming compns. containing aromatic aldehyde, imino compound and, for thermal recording materials)
IT 97-51-8 99-61-6 100-83-4 104-88-1, uses and miscellaneous 123-08-0 623-27-8 874-42-0 1122-91-4 30525-89-4
(color-forming compns. containing imino compound and, for thermal recording materials)

L62 ANSWER 18 OF 18 HCAPLUS COPYRIGHT 2006 ACS on STN

ACCESSION NUMBER: 1963:412976 HCAPLUS
DOCUMENT NUMBER: 59:12976
ORIGINAL REFERENCE NO.: 59:2303a-c
TITLE: Diffusion coefficients of carbonyls in Raman spectroscopy
AUTHOR(S): Michel, Gilbert
CORPORATE SOURCE: Inst. Chim. Anal., Liege, Belg.
SOURCE: Bulletin des Societes Chimiques Belges (1963),

72, 125-48

CODEN: BSCBAG; ISSN: 0037-9646

DOCUMENT TYPE:

Journal

LANGUAGE:

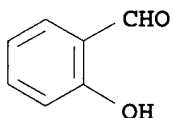
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AB Correction terms are required to make intensity data taken on a variety of Raman spectrometers more directly comparable: exciting frequency and temperature, direction of exciting radiation, spectral response of detection system, n , and absorbance of diffusing medium. Tabulated data are expressed in terms of an internal standard (CCl₄:459) by using Hg4358 at $23 \pm 0.2^\circ$ and a tube, diameter = 1 cm., length = 20 cm. of glass of $n_{20D} = 1.473$. Diffusion coeffs. are based on the average of 3-8 results on each compound. Expressing the results as a diffusion coefficient, the numerical values are given as the mean of a number of examples of each class, when the spread among members of the class is small: aliphatic esters, 0.077; aliphatic ketones, 0.091; alicyclic ketones 0.14. Thirteen tables give data on .apprx.130 compds. containing C:O and combinations of C:O and C:C, together with comparisons of other literature data when available. The data show the diffusion coefficient to be exalted in the sequence ester, ketone, aldehyde, and unsaturate. The coefficient for ketones runs from 0.082 in acetone to 3.1 in p-Me benzophenone; from 0.078 in EtOAc to 12.3 in cinnamaldehyde. 37 references.

IT 90-02-8, Salicylaldehyde 123-72-8, Butyraldehyde
(spectrum (Raman) of, line intensities of carbonyl group in, scattering coeffs. for)

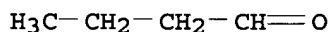
RN 90-02-8 HCAPLUS

CN Benzaldehyde, 2-hydroxy- (9CI) (CA INDEX NAME)



RN 123-72-8 HCAPLUS

CN Butanal (9CI) (CA INDEX NAME)



CC 10 (Spectra and Some Other Optical Properties)

IT 60-01-5, Butyrin, tri- 62-23-7, Benzoic acid, p-nitro-
64-19-7, Acetic acid 70-11-1, Acetophenone, 2-bromo- 75-07-0,
Acetaldehyde 76-49-3, Borneol, acetate 78-59-1,
2-Cyclohexen-1-one, 3,5,5-trimethyl- 78-94-4, 3-Buten-2-one
78-95-5, 2-Propanone, chloro- 79-20-9, Acetic acid, methyl ester
80-62-6, Methyl methacrylate 89-71-4, o-Toluic acid, methyl
ester 89-98-5, Benzaldehyde, o-chloro- 90-02-8,
Salicylaldehyde 92-91-1, Acetophenone, 4'-phenyl- 94-30-4,
p-Anisic acid, ethyl ester 96-22-0, 3-Pentanone 98-86-2,
Acetophenone 98-88-4, Benzoyl chloride 99-36-5, m-Toluic acid,
methyl ester 99-75-2, p-Toluic acid, methyl ester 99-90-1,
Acetophenone, 4'-bromo- 99-91-2, Acetophenone, 4'-chloro-
99-92-3, Acetophenone, 4'-amino- 99-93-4, Acetophenone,
4'-hydroxy- 100-06-1, Acetophenone, 4'-methoxy- 100-19-6,
Acetophenone, 4'-nitro- 100-47-0, Benzonitrile 100-52-7,
Benzaldehyde 101-97-3, Acetic acid, phenyl-, ethyl ester

103-36-6, Cinnamic acid, ethyl ester 103-79-7, 2-Propanone, phenyl- 104-88-1, Benzaldehyde, p-chloro- 105-37-3, Propionic acid, ethyl ester 105-39-5, Acetic acid, chloro-, ethyl ester 105-53-3, Malonic acid, diethyl ester 105-54-4, Butyric acid, ethyl ester 107-87-9, 2-Pentanone 108-05-4, Vinyl acetate 108-10-1, 2-Pentanone, 4-methyl- 108-83-8, 4-Heptanone, 2,6-dimethyl- 109-49-9, 5-Hexen-2-one 110-13-4, 2,5-Hexanedione 118-61-6, Salicylic acid, ethyl ester 119-61-9, Benzophenone 120-47-8, Benzoic acid, p-hydroxy-, ethyl ester 120-92-3, Cyclopentanone 122-00-9, Acetophenone, 4'-methyl- 122-57-6, 3-Buten-2-one, 4-phenyl- 122-79-2, Acetic acid, phenyl ester 123-08-0, Benzaldehyde, p-hydroxy- 123-11-5, p-Anisaldehyde 123-19-3, 4-Heptanone 123-42-2, 2-Pentanone, 4-hydroxy-4-methyl- 123-72-8, Butyraldehyde 123-86-4, Acetic acid, butyl ester 134-84-9, Benzophenone, 4-methyl- 135-02-4, o-Anisaldehyde 140-88-5, Acrylic acid, ethyl ester 462-18-0, 7-Tridecanone 504-20-1, 2,5-Heptadien-4-one, 2,6-dimethyl- 515-84-4, Acetic acid, trichloro-, ethyl ester 532-27-4, Acetophenone, 2-chloro- 563-80-4, 2-Butanone, 3-methyl- 565-80-0, 3-Pentanone, 2,4-dimethyl- 577-59-3, Acetophenone, 2'-nitro- 579-74-8, Acetophenone, 2'-methoxy- 587-04-2, Benzaldehyde, m-chloro- 591-31-1, m-Anisaldehyde 606-27-9, Benzoic acid, o-nitro-, methyl ester 606-45-1, o-Anisic acid, methyl ester 610-94-6, Benzoic acid, o-bromo-, methyl ester 610-96-8, Benzoic acid, o-chloro-, methyl ester 610-97-9, Benzoic acid, o-iodo-, methyl ester 611-97-2, Benzophenone, 4,4'-dimethyl- 618-32-6, Benzoyl bromide 618-91-7, Benzoic acid, m-iodo-, methyl ester 618-95-1, Benzoic acid, m-nitro-, methyl ester 619-42-1, Benzoic acid, p-bromo-, methyl ester 619-44-3, Benzoic acid, p-iodo-, methyl ester 623-50-7, Glycolic acid, ethyl ester 625-33-2, 3-Penten-2-one 638-10-8, Crotonic acid, 3-methyl-, ethyl ester 814-78-8, 3-Buten-2-one, 3-methyl- 1195-79-5, 2-Norbornanone, 1,3,3-trimethyl- 1754-55-8, Benzoic acid, 2,4,6-trimethyl-, ethyl ester 2142-73-6, Acetophenone, 2',5'-dimethyl- 2476-37-1, Acetophenone, 2',5'-dichloro- 2623-45-2, Acetophenone, 2-chloro-2',4'-dimethyl- 3637-01-2, Acetophenone, 3',4'-dimethyl- 4170-30-3, Crotonaldehyde 7335-27-5, Benzoic acid, p-chloro-, ethyl ester 10259-22-0, m-Anisic acid, ethyl ester 10544-63-5, Crotonic acid, ethyl ester 24398-88-7, Benzoic acid, m-bromo-, ethyl ester 89897-92-7, Crotonic acid, 3-methyl-, vinyl ester

(spectrum (Raman) of, line intensities of carbonyl group in, scattering coeffs. for)

=> d. que 153

L3	376	SEA FILE=REGISTRY ABB=ON	PLU=ON	90-02-8/CRN
L4	25	SEA FILE=REGISTRY ABB=ON	PLU=ON	100-83-4/CRN
L5	214	SEA FILE=REGISTRY ABB=ON	PLU=ON	123-72-8/CRN
L6	1	SEA FILE=REGISTRY ABB=ON	PLU=ON	ETHANOL/CN
L7	1	SEA FILE=REGISTRY ABB=ON	PLU=ON	METHANOL/CN
L9	1	SEA FILE=REGISTRY ABB=ON	PLU=ON	90-02-8/RN
L10	1	SEA FILE=REGISTRY ABB=ON	PLU=ON	100-83-4/RN
L11	1	SEA FILE=REGISTRY ABB=ON	PLU=ON	123-72-8/RN
L15	56174	SEA FILE=REGISTRY ABB=ON	PLU=ON	46.248/RID
L16	1779	SEA FILE=REGISTRY ABB=ON	PLU=ON	L15 AND PMS/CI
L23	2	SEA FILE=REGISTRY ABB=ON	PLU=ON	(L3 OR L4) AND L5
L24	1	SEA FILE=HCAPLUS ABB=ON	PLU=ON	L23
L25	552	SEA FILE=HCAPLUS ABB=ON	PLU=ON	L3

L26 41 SEA FILE=HCAPLUS ABB=ON PLU=ON L4
 L27 426 SEA FILE=HCAPLUS ABB=ON PLU=ON L5
 L28 3 SEA FILE=HCAPLUS ABB=ON PLU=ON (L25 OR L26) AND L27
 L29 11427 SEA FILE=HCAPLUS ABB=ON PLU=ON L9
 L30 2435 SEA FILE=HCAPLUS ABB=ON PLU=ON L10
 L31 12010 SEA FILE=HCAPLUS ABB=ON PLU=ON L11
 L32 410 SEA FILE=HCAPLUS ABB=ON PLU=ON (L29 OR L30) AND L31
 L33 7 SEA FILE=HCAPLUS ABB=ON PLU=ON L32 AND LITHOG?
 L34 4 SEA FILE=HCAPLUS ABB=ON PLU=ON L32 AND RADIAT?
 L35 9 SEA FILE=HCAPLUS ABB=ON PLU=ON L33 OR L34
 L36 191327 SEA FILE=HCAPLUS ABB=ON PLU=ON L6
 L37 133365 SEA FILE=HCAPLUS ABB=ON PLU=ON L7
 L38 217 SEA FILE=HCAPLUS ABB=ON PLU=ON L9/DP
 L39 18 SEA FILE=HCAPLUS ABB=ON PLU=ON L10/DP
 L40 111 SEA FILE=HCAPLUS ABB=ON PLU=ON L11/DP
 L41 5 SEA FILE=HCAPLUS ABB=ON PLU=ON (L38 OR L39) AND L40
 L42 14 SEA FILE=HCAPLUS ABB=ON PLU=ON L24 OR L28 OR L33 OR
 L34 OR L35 OR L41
 L43 1580 SEA FILE=HCAPLUS ABB=ON PLU=ON L16
 L44 131 SEA FILE=HCAPLUS ABB=ON PLU=ON L43 (L) COMPOSITION?
 L45 2 SEA FILE=HCAPLUS ABB=ON PLU=ON L44 AND LITHOG?
 L46 71 SEA FILE=HCAPLUS ABB=ON PLU=ON L32 AND (L36 OR L37)
 L47 0 SEA FILE=HCAPLUS ABB=ON PLU=ON L46 AND PHOTOG?/SC, SX

 L48 0 SEA FILE=HCAPLUS ABB=ON PLU=ON L46 AND PHOTOG?
 L50 20 SEA FILE=HCAPLUS ABB=ON PLU=ON L44 AND PHOTOG?/SC
 L51 14 SEA FILE=HCAPLUS ABB=ON PLU=ON L42 OR L47 OR L48
 L52 20 SEA FILE=HCAPLUS ABB=ON PLU=ON L45 OR L50
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=> d 153 1-20 ibib abs hitstr hitind

L53 ANSWER 1 OF 20 HCAPLUS COPYRIGHT 2006 ACS on STN
 ACCESSION NUMBER: 2005:155470 HCAPLUS
 DOCUMENT NUMBER: 142:249065
 TITLE: Nanoparticle-filled stereolithographic resins
 INVENTOR(S): Steinmann, Bettina; Steinmann, Alfred
 PATENT ASSIGNEE(S): 3D Systems, Inc., USA
 SOURCE: Eur. Pat. Appl., 14 pp.
 CODEN: EPXXDW
 DOCUMENT TYPE: Patent
 LANGUAGE: English
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
EP 1508834	A2	20050223	EP 2004-254005	2004 0702
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, PL, SK, HR				
US 2005040562	A1	20050224	US 2003-644299	2003 0819
JP 2005060673	A2	20050310	JP 2004-187526	2004

PRIORITY APPLN. INFO.:

US 2003-644299

A

0625

2003

0819

AB A liquid radiation-curable composition useful for the production of three dimensional articles by stereolithog. comprises: (a) at least one free-radical polymerizing organic substance; (b) at least one free-radical polymerization initiator; (d) at least one filler comprising silica-type nanoparticles suspended in the radiation-curable composition; (d) at least one cationically polymerizing organic substance; (e) at least one cationic polymerization initiator; (f) optionally, at least one hydroxyl-functional compound; and (g) optionally, at least one type of microparticle filler.

IT 189243-74-1, Nanocryl XP 21/0765

(silica-filled; liquid radiation curable **composition** for nanoparticle-filled stereolithog. resins containing)

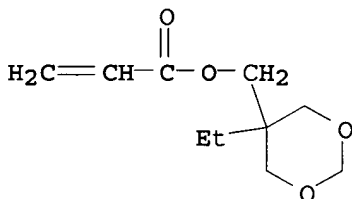
RN 189243-74-1 HCAPLUS

CN 2-Propenoic acid, (5-ethyl-1,3-dioxan-5-yl)methyl ester, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 66492-51-1

CMF C10 H16 O4



IC ICM G03F007-00

ICS G03F007-004

CC 74-6 (Radiation Chemistry, Photochemistry, and **Photographic** and Other Reprographic Processes)

IT 36446-02-3, Nanocryl XP 21/1045 57592-67-3, Nanocryl XP 21/0768

189243-74-1, Nanocryl XP 21/0765

(silica-filled; liquid radiation curable **composition** for nanoparticle-filled stereolithog. resins containing)

L53 ANSWER 2 OF 20 HCAPLUS COPYRIGHT 2006 ACS on STN

ACCESSION NUMBER: 2004:695482 HCAPLUS

DOCUMENT NUMBER: 141:215780

TITLE: Transparent crosslinked resin composition containing glass filler

INVENTOR(S): Fukunishi, Masaaki; Shibahara, Sumio

PATENT ASSIGNEE(S): Sumitomo Bakelite Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 13 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.

KIND

DATE

APPLICATION NO.

DATE

JP 2004238532 A2 20040826 JP 2003-29850

2003
0206

PRIORITY APPLN. INFO.:

JP 2003-29850

2003
0206

AB The crosslinked composition contains a glass filler and a transparent resin comprising 1-99 weight% of a reactive monomer and/or oligomer and 1-99 weight% of an amorphous thermoplastic resin, which shows $\geq 80\%$ transmission of light with wavelength 550 nm at 100- μm thickness. The composition is used as an optical sheet, a substrate for a display device, and an active matrix liquid crystal display device substrate, i.e., alternatives for glass substrates in optical devices.

IT 573718-30-6P

(transparent crosslinked resin **composition** containing glass filler as alternative for glass substrate in optical devices)

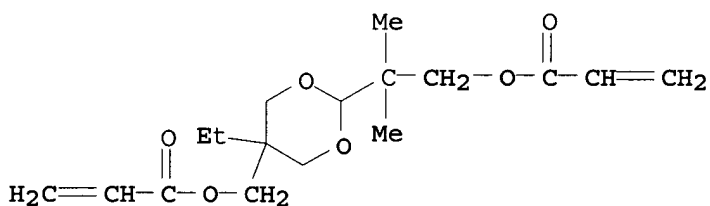
RN 573718-30-6 HCAPLUS

CN 2-Propenoic acid, bicyclo[2.2.1]heptane-2,3-diylbis(methylene) ester, polymer with [2-[1,1-dimethyl-2-[(1-oxo-2-propenyl)oxy]ethyl]-5-ethyl-1,3-dioxan-5-yl]methyl 2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 87320-05-6

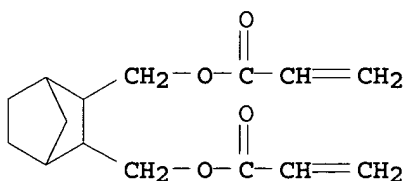
CMF C17 H26 O6



CM 2

CRN 79886-78-5

CMF C15 H20 O4



IC ICM C08L101-00

ICS C08K003-40; C08K005-101; G02F001-1333; H05B033-02; H05B033-14

CC 74-13 (Radiation Chemistry, Photochemistry, and

Photographic and Other Reprographic Processes)

Section cross-reference(s): 38, 57, 73

IT 573718-30-6P

(transparent crosslinked resin **composition** containing glass filler as alternative for glass substrate in optical devices)

L53 ANSWER 3 OF 20 HCAPLUS COPYRIGHT 2006 ACS on STN

ACCESSION NUMBER: 2004:695416 HCAPLUS

DOCUMENT NUMBER: 141:215718

TITLE: Coating composition containing photo-curable resin and thermal printing material

INVENTOR(S): Makabe, Yoshie; Kanda, Akira; Oya, Keiji

PATENT ASSIGNEE(S): Asahi Denka Kogyo K. K., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 18 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2004237515	A2	20040826	JP 2003-27952	2003 0205

PRIORITY APPLN. INFO.:

JP 2003-27952

2003
0205

AB The composition contains (A) a color-former, (B) an organic color developer, (C) a photocurable resin composition, (D) a photo-curing agent, and (E) alicyclic amine and/or alicyclic amide compound bearing N in cyclic structure as a coloration preventing agent. Coated thermal printing material manufactured by coating and photo-curing the composition is also claimed. Coloration on photocuring is prevented, and the material gives clear color images.

IT 116321-27-8P, Kayarad R 604 homopolymer

(coating **composition** containing photo-curable resin for thermal printing material)

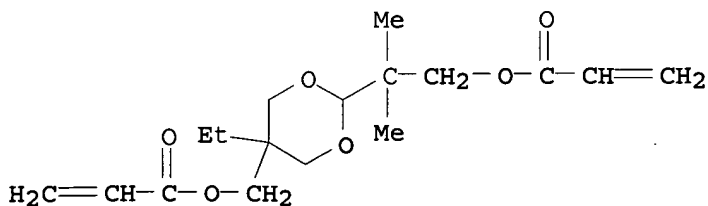
RN 116321-27-8 HCAPLUS

CN 2-Propenoic acid, [2-[1,1-dimethyl-2-[(1-oxo-2-propenyl)oxy]ethyl]-5-ethyl-1,3-dioxan-5-yl]methyl ester, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 87320-05-6

CMF C17 H26 O6



IC ICM B41M005-30
ICS B41M005-26
CC 74-7 (Radiation Chemistry, Photochemistry, and
Photographic and Other Reprographic Processes)
Section cross-reference(s): 38
IT 28628-65-1P, Neopentyl glycol diacrylate homopolymer
57592-67-3P, 1,6-Hexanediol diacrylate homopolymer 88583-06-6P,
Kayarad DPHA homopolymer **116321-27-8P**, Kayarad R 604
homopolymer 125086-52-4P 744222-17-1P
(coating **composition** containing photo-curable resin for
thermal printing material)

L53 ANSWER 4 OF 20 HCAPLUS COPYRIGHT 2006 ACS on STN

ACCESSION NUMBER: 2003:492523 HCAPLUS

DOCUMENT NUMBER: 139:60447

TITLE: Norbornene-based copolymer for photoresist,
preparation method thereof, and photoresist
composition comprising the same

INVENTOR(S): Han, Eun Sil; Moon, Bong Seok; Shin, Jung Han;
Han, Ouck

PATENT ASSIGNEE(S): Samsung Electronics Co., Ltd., S. Korea

SOURCE: U.S. Pat. Appl. Publ., 13 pp.

CODEN: USXXCO

DOCUMENT TYPE: Patent

LANGUAGE: English

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO. -----	KIND ----	DATE -----	APPLICATION NO. -----	DATE
US 2003118933	A1	20030626	US 2002-246474	2002 0919
US 6753127	B2	20040622		
KR 2003036948	A	20030512	KR 2001-67898	2001 1101
TW 593367	B	20040621	TW 2002-91104789	2002 0313
JP 2003183327	A2	20030703	JP 2002-307209	2002 1022
PRIORITY APPLN. INFO.:			KR 2001-67898	A 2001 1101

AB Disclosed is an norbornene-based copolymer for photoresist, a
preparation method thereof, and a photoresist composition comprising the
same. The copolymer of the present invention exhibits high
transparency to light of 193 nm wavelength and an excellent
etching resistance, excellent resolution due to the remarkable
difference between light-exposed part and light-unexposed part in
the dissolving rate and excellent adhesion to the substrate due to
very hydrophilic diketone group of its own. As a result, the
copolymer of the present invention is very useful as ArF exposure
photoresist material in the fabrication of semiconductor devices.

IT 547766-01-8 547766-03-0 547766-04-1

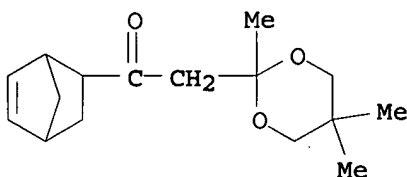
(copolymer in photoresist **composition**)

RN 547766-01-8 HCAPLUS
 CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, polymer with
 1-bicyclo[2.2.1]hept-5-en-2-yl-1,3-butanedione,
 1-bicyclo[2.2.1]hept-5-en-2-yl-2-(2,5,5-trimethyl-1,3-dioxan-2-
 yl)ethanone and 1,1-dimethylethyl bicyclo[2.2.1]hept-5-ene-2-
 carboxylate (9CI) (CA INDEX NAME)

CM 1

CRN 547765-97-9

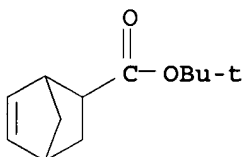
CMF C16 H24 O3



CM 2

CRN 154970-45-3

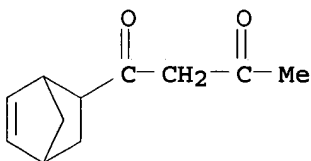
CMF C12 H18 O2



CM 3

CRN 52204-67-8

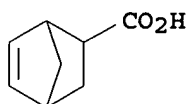
CMF C11 H14 O2



CM 4

CRN 120-74-1

CMF C8 H10 O2



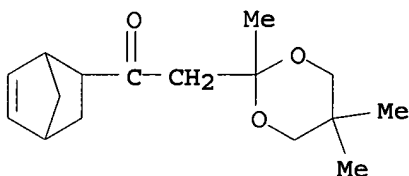
RN 547766-03-0 HCAPLUS

CN 1,3-Butanedione, 1-bicyclo[2.2.1]hept-5-en-2-yl-, polymer with bicyclo[2.2.1]hept-2-ene and 1-bicyclo[2.2.1]hept-5-en-2-yl-2-(2,5,5-trimethyl-1,3-dioxan-2-yl)ethanone (9CI) (CA INDEX NAME)

CM 1

CRN 547765-97-9

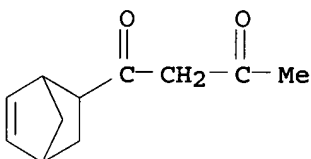
CMF C16 H24 O3



CM 2

CRN 52204-67-8

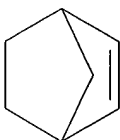
CMF C11 H14 O2



CM 3

CRN 498-66-8

CMF C7 H10



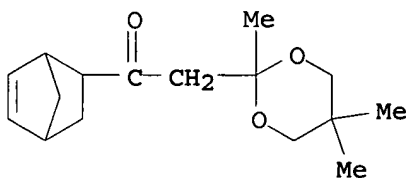
RN 547766-04-1 HCAPLUS

CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 1,1-dimethylethyl ester, polymer with bicyclo[2.2.1]hept-2-ene, 1-bicyclo[2.2.1]hept-5-en-2-yl-1,3-butanedione and 1-bicyclo[2.2.1]hept-5-en-2-yl-2-(2,5,5-trimethyl-1,3-dioxan-2-yl)ethanone (9CI) (CA INDEX NAME)

CM 1

CRN 547765-97-9

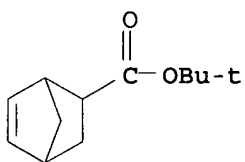
CMF C16 H24 O3



CM 2

CRN 154970-45-3

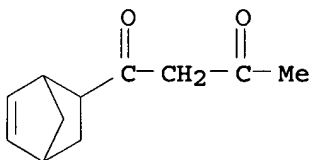
CMF C12 H18 O2



CM 3

CRN 52204-67-8

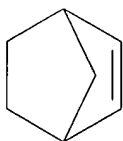
CMF C11 H14 O2



CM 4

CRN 498-66-8

CMF C7 H10



IC ICM G03F007-038

ICS G03F007-30; G03F007-38; C08F004-06; C08F004-40; C08F004-42;
 C08F010-00; C08F132-08; C08F136-00; C08F232-08; C07C049-105;
 C07C049-293; C07C049-297; C07C049-385; C07C049-403;
 C07D323-04; C07D319-12

INCL 430270100; 430326000; 430327000; 430330000; 430905000; 430914000;
 526280000; 549367000; 549454000; 568374000

CC 74-5 (Radiation Chemistry, Photochemistry, and
Photographic and Other Reprographic Processes)

IT 107-21-1, Ethylene glycol, reactions 126-30-7,
 2,2-Dimethyl-1,3-propane diol 141-78-6, Ethylacetate, reactions
 504-63-2, 1,3-Propylenediol 2916-31-6, 2,2-Dimethyl-1,3-
 dioxolane 5063-03-6, 2-Acetyl-5-norbornene 195154-78-0
 547765-96-8 547765-97-9 547765-98-0 547765-99-1
 547766-00-7 **547766-01-8** 547766-02-9
547766-03-0 547766-04-1
 (copolymer in photoresist **composition**)

REFERENCE COUNT: 3 THERE ARE 3 CITED REFERENCES AVAILABLE
 FOR THIS RECORD. ALL CITATIONS AVAILABLE
 IN THE RE FORMAT

L53 ANSWER 5 OF 20 HCAPLUS COPYRIGHT 2006 ACS on STN

ACCESSION NUMBER: 2003:222222 HCAPLUS

DOCUMENT NUMBER: 138:262687

TITLE: Chemically amplified negative photoresist, and
 photoresist composition

INVENTOR(S): Lee, Beom-Wook; Lim, Ik-Chul; Yoo, Seung-Joon

PATENT ASSIGNEE(S): Samsung SDI Co., Ltd., S. Korea

SOURCE: U.S. Pat. Appl. Publ., 14 pp.
 CODEN: USXXCO

DOCUMENT TYPE: Patent

LANGUAGE: English

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
-----	----	-----	-----	
US 2003054285	A1	20030320	US 2002-92846	2002 0307
US 6872502	B2	20050329		
KR 2002078485	A	20021019	KR 2001-17601	2001 0403
PRIORITY APPLN. INFO.:			KR 2001-17601	A 2001 0403

OTHER SOURCE(S): MARPAT 138:262687
 GI

* STRUCTURE DIAGRAM TOO LARGE FOR DISPLAY - AVAILABLE VIA OFFLINE PRINT
 *

AB A polymer for a chemical amplified neg. photoresist and a photoresist
 composition are provided. A representative polymer of the invention is
 a compound of R1C(=CH2)R2R3 or R1C(+CH2)R4R5 (R1 = H, CH3; R2,4

$= (R)\alpha (CH_2)\beta R', (R)\alpha [(CH_2)\gamma O]\delta R'$;
 $R = CO, CO_2, O, OCO, OCO_2$; $R' = O, CO_2, OCO_2$; $\alpha = 0, 1$;
 $\beta = 0-5$; $\gamma = 1, 2$; $\delta = 1-5$; $R_3 = R_6R_7COR_8OR_9$,
 formula I, II, III (R_6 which combines an acetal compound and a vinyl
 compound, is a C1-C5 saturated alkyl, C1-C5 ether, a C1-C5 carbonyl;
 $R_7-11 = H$, C1-C5 saturated alkyls, C1-C5 ethers, C1-C5 carbonyl
 groups, C1-C5 alc. groups; $m = 1-5$); R_5 is represented by formula
 IV ($R_{12,13} = H$ or OH ; $*$ = the bonding site at which the R_4 group
 is bonded)).

IT 502699-60-7P 502699-63-0P

(preparation of polymer for chemical amplified neg. photoresist, and
 photoresist composition)

RN 502699-60-7 HCAPLUS

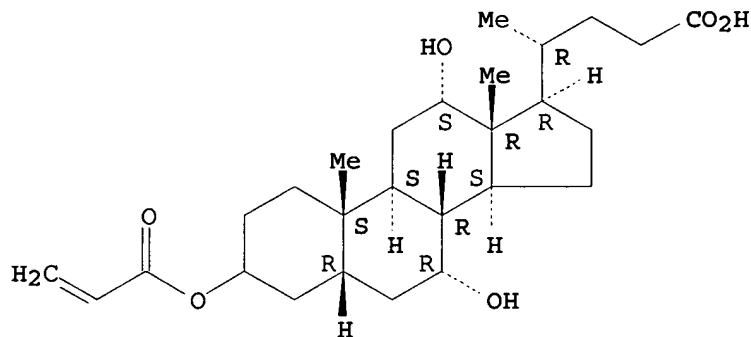
CN Cholan-24-oic acid, 7,12-dihydroxy-3-[(1-oxo-2-propenyl)oxy]-,
 (5 β ,7 α ,12 α)-, polymer with 2-(1,3-dioxan-2-
 yl)ethyl 2-propenoate and 2-hydroxyethyl 2-propenoate (9CI) (CA
 INDEX NAME)

CM 1

CRN 502699-57-2

CMF C27 H42 O6

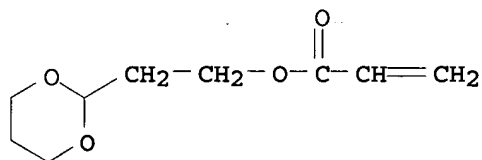
Absolute stereochemistry.



CM 2

CRN 14180-36-0

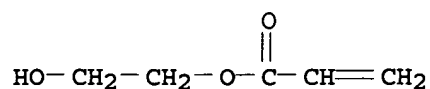
CMF C9 H14 O4



CM 3

CRN 818-61-1

CMF C5 H8 O3

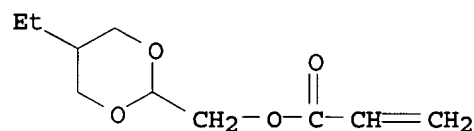


RN 502699-63-0 HCAPLUS
 CN Cholan-24-oic acid, 7,12-dihydroxy-3-[(1-oxo-2-propenyl)oxy]-, (5 α ,7 α ,12 α)-, polymer with (5-ethyl-1,3-dioxan-2-yl)methyl 2-propenoate, 2-hydroxyethyl 2-propenoate and 2-propenoic acid (9CI) (CA INDEX NAME)

CM 1

CRN 502699-62-9

CMF C10 H16 O4

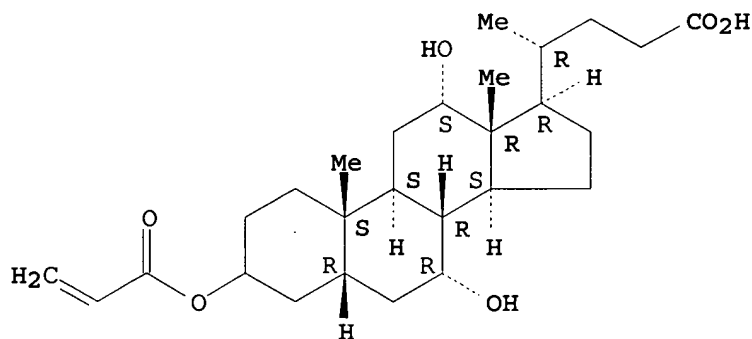


CM 2

CRN 502699-57-2

CMF C27 H42 O6

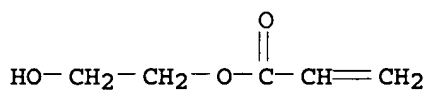
Absolute stereochemistry.



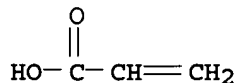
CM 3

CRN 818-61-1

CMF C5 H8 O3



CM 4

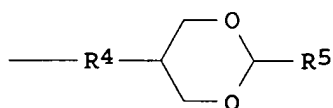
CRN 79-10-7
CMF C3 H4 O2

IC ICM G03F007-038
 INCL 430270100; 526270000; 526266000; 526280000; 549369000; 549357000
 CC 74-5 (Radiation Chemistry, Photochemistry, and
Photographic and Other Reprographic Processes)
 Section cross-reference(s): 35, 38
 IT 502699-58-3P 502699-59-4P **502699-60-7P** 502699-61-8P
502699-63-0P 502699-64-1P
 (preparation of polymer for chemical amplified neg. photoresist, and
 photoresist **composition**)
 REFERENCE COUNT: 21 THERE ARE 21 CITED REFERENCES AVAILABLE
 FOR THIS RECORD. ALL CITATIONS AVAILABLE
 IN THE RE FORMAT

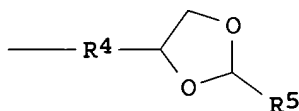
L53 ANSWER 6 OF 20 HCAPLUS COPYRIGHT 2006 ACS on STN
 ACCESSION NUMBER: 2002:755238 HCAPLUS
 DOCUMENT NUMBER: 137:286456
 TITLE: Monomer and polymer for photoresist,
 photoresist composition, and phosphor layer
 composition for color cathode ray tube
 INVENTOR(S): Lee, Beom-Wook; Lim, Ik-Chul; Yoo, Seung-Joon
 PATENT ASSIGNEE(S): Samsung SDI Co., Ltd., S. Korea
 SOURCE: U.S. Pat. Appl. Publ., 11 pp.
 CODEN: USXXCO
 DOCUMENT TYPE: Patent
 LANGUAGE: English
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 2002143130	A1	20021003	US 2002-76317	2002 0214
US 6699951	B2	20040302		
KR 2002077948	A	20021018	KR 2001-17600	2001 0403
PRIORITY APPLN. INFO.:			KR 2001-17600	A 2001 0403

GI



I



II

AB Disclosed are a monomer, a polymer for a photoresist, a photoresist composition and a phosphor layer for a cathode ray tube. The polymer has the formula: $[(CH_2-CR_1R_8-R_9)_a-(CH_2-CR_1R_6-R_7)_b-(CH_2-CR_1R_2-R_3)_c]_n$ ($R_1 = H, CH_3$; $R_2 = (R)\alpha (CH_2)\beta R'$ or $(R)\beta ((CH_2)mO)\gamma R'$; $R = CO, CO_2, O, OCO, OCO_2$; $R' = O, CO_2, OCO_2$; $\alpha = 0, 1$; $\beta = 0-5$; $m = 1, 2$; $\gamma = 1-5$; $R_3 = I$ or II ; R_4 , which combines an acetal compound and a vinyl compound, $= C_1-C_5$ alkyl, ether, carbonyl; $R_5 = C_1-C_5$ alkyl, ether, carbonyl; $R_6, 8 =$ single bond, $(R)\alpha (CH_2)\beta R'$ or $(R)\beta ((CH_2)mO)\gamma R'$; $R_7 =$ hydroxyl group; $R_9 =$ carboxyl group; $a, b,$ and c each represent the mole ratio of its corresponding monomer, a and $b = 0-0.99$, and $c = 0.01-0.3$; and $n =$ d.p. of each polymer and has a value of ≥ 2). The present invention relates to photoresist composition for a color cathode ray tube which causes no environmental pollution and has good storage stability and high sensitivity.

IT 464918-96-5P 464918-97-6P

(monomer and polymer for photoresist composition, and phosphor layer composition for color cathode ray tube)

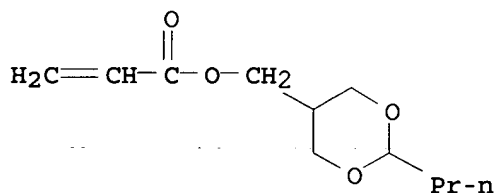
RN 464918-96-5 HCAPLUS

CN 2-Propenoic acid, 2-hydroxyethyl ester, polymer with (2-propyl-1,3-dioxan-5-yl)methyl 2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 464918-93-2

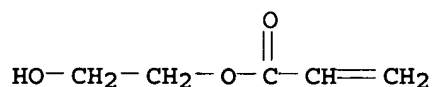
CMF C11 H18 O4



CM 2

CRN 818-61-1

CMF C5 H8 O3

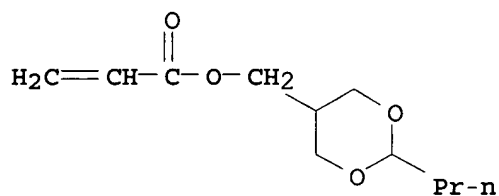


RN 464918-97-6 HCAPLUS
 CN 2-Propenoic acid, polymer with 2-hydroxyethyl 2-propenoate and
 (2-propyl-1,3-dioxan-5-yl)methyl 2-propenoate (9CI) (CA INDEX
 NAME)

CM 1

CRN 464918-93-2

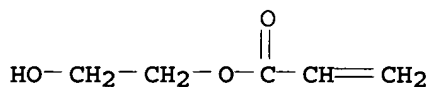
CMF C11 H18 O4



CM 2

CRN 818-61-1

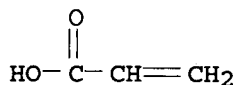
CMF C5 H8 O3



CM 3

CRN 79-10-7

CMF C3 H4 O2



IC ICM C08F224-00

ICS C07D319-06; C07D317-44

INCL 526266000

CC 74-5 (Radiation Chemistry, Photochemistry, and
Photographic and Other Reprographic Processes)
 Section cross-reference(s): 35, 38

IT 464918-94-3P 464918-95-4P **464918-96-5P**

464918-97-6P

(monomer and polymer for photoresist **composition**, and
 phosphor layer **composition** for color cathode ray tube)

L53 ANSWER 7 OF 20 HCAPLUS COPYRIGHT 2006 ACS on STN

ACCESSION NUMBER: 2001:524704 HCAPLUS

DOCUMENT NUMBER: 135:114408

TITLE: Photoelectrochemical cell comprising polymer electrolyte composition formed by polymerizing ionic liquid crystal monomer

INVENTOR(S): Ono, Michio

PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan

SOURCE: Eur. Pat. Appl., 43 pp.

CODEN: EPXXDW

DOCUMENT TYPE: Patent

LANGUAGE: English

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
EP 1116769	A2	20010718	EP 2001-100999	2001 0117
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO				
JP 2001202995	A2	20010727	JP 2000-8054	2000 0117
US 2002034690	A1	20020321	US 2001-759363	2001 0116
US 6727023	B2	20040427		
PRIORITY APPLN. INFO.:			JP 2000-8054	A 2000 0117

OTHER SOURCE(S): MARPAT 135:114408

AB Disclosed is an electrolyte composition comprising a polymer compound formed by polymerizing an ionic liquid crystal monomer containing at least one polymerizable group. Also disclosed are an electrochem. cell, a nonaq. secondary cell and a photoelectrochem. cell, each comprising the electrolyte composition. In accordance with the present invention, an electrolyte which does not substantially volatilize and exhibits excellent charge-transporting properties can be obtained, making it possible to obtain a photoelectrochem. cell having excellent photoelec. conversion properties and less deterioration of properties with time. Further, a lithium ion-conducting material having an extremely high ionic conductivity at low temps. can be obtained.

IT 350507-60-7P 350507-61-8P

(electrolyte composition comprising polymer compound formed by polymerizing of ionic liquid crystal monomer for photoelectrochem. cell application)

RN 350507-60-7 HCAPLUS

CN Pyridinium, 4-(trans-5-decyl-1,3-dioxan-2-yl)-1-(19-oxo-3,6,9,12,15,18-hexaoxaheneicos-20-en-1-yl)-, iodide, homopolymer (9CI) (CA INDEX NAME)

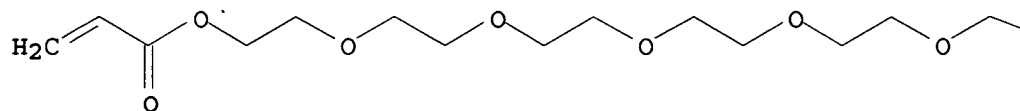
CM 1

CRN 350507-51-6

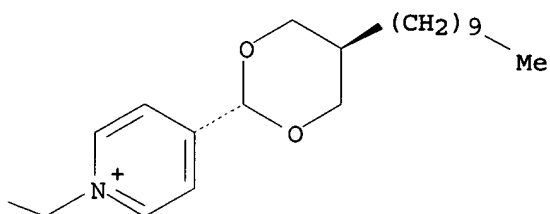
CMF C34 H58 N O9 . I

Relative stereochemistry.

PAGE 1-A



PAGE 1-B



RN 350507-61-8 HCAPLUS

CN Pyridinium, 1,1'-(3,6,9,12,15-pentaoxaheptadecane-1,17-diyl)bis[4-[trans-5-[10-[(1-oxo-2-propenyl)oxy]decyl]-1,3-dioxan-2-yl]-, diiodide, homopolymer (9CI) (CA INDEX NAME)

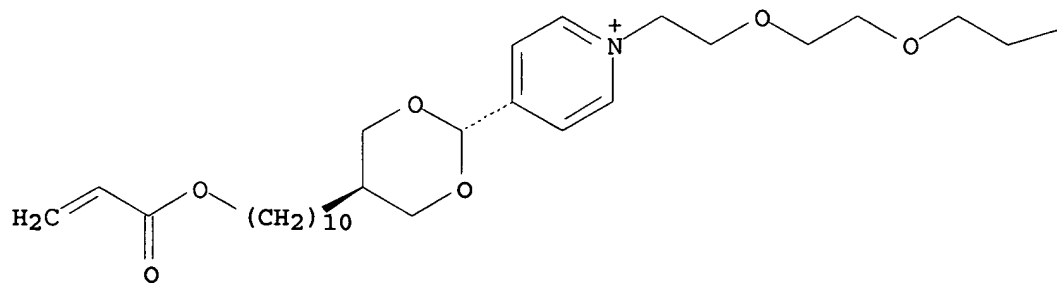
CM 1

CRN 350507-54-9

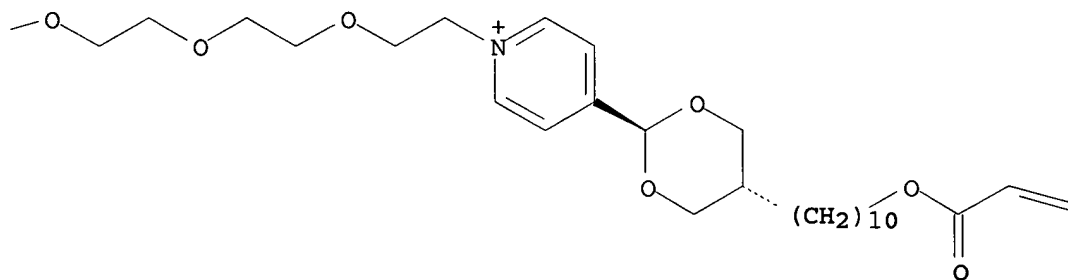
CMF C56 H90 N2 O13 . 2 I

Relative stereochemistry.

PAGE 1-A

● 2 I⁻

PAGE 1-B



PAGE 1-C

=CH₂

IC ICM C09K019-00
 ICS C09K019-38; H01G009-20
 CC 74-1 (Radiation Chemistry, Photochemistry, and
 Photographic and Other Reprographic Processes)
 Section cross-reference(s): 72
 IT 350507-60-7P 350507-61-8P 350507-62-9P
 350507-63-0P 350507-64-1P
 (electrolyte **composition** comprising polymer compound formed
 by polymerizing of ionic liquid crystal monomer for photoelectrochem.
 cell application)

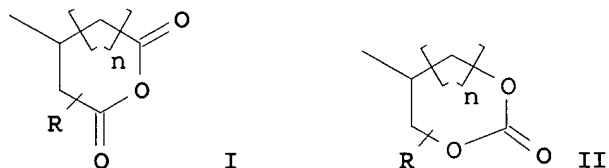
L53 ANSWER 8 OF 20 HCAPLUS COPYRIGHT 2006 ACS on STN

USHA SHRESTHA EIC 1700 REM 4B28

ACCESSION NUMBER: 2001:62632 HCAPLUS
 DOCUMENT NUMBER: 134:139210
 TITLE: Resin for resists and chemical amplification
 resist composition
 INVENTOR(S): Fujiwara, Tadayuki; Wakisaka, Yukiya; Toyama,
 Masayuki; Murata, Tadashi
 PATENT ASSIGNEE(S): Mitsubishi Rayon Co., Ltd., Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 7 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2001022073	A2	20010126	JP 1999-198161	1999 0712
PRIORITY APPLN. INFO.:			JP 1999-198161	1999 0712

GI



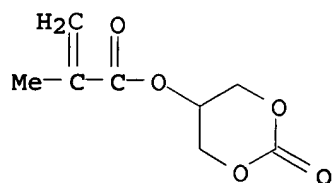
AB The title resin, which becomes soluble in aqueous alkali solns. by the action of acid, comprises a monomer unit having ≥ 1 structure selected from I and II ($R = H$ or alkyl; $n = 0-4$) and the chemical amplification resist composition contains the resin and a photoacid generator. The resin and resist composition show high adhesion to substrates and photosensitivity and are especially useful in deep UV excimer laser and electron beam lithog.

IT 321660-48-4P 321660-50-8P
 (chemical amplification resist composition for lithog.)

RN 321660-48-4 HCAPLUS
 CN 2-Propenoic acid, 2-methyl-, 2-oxo-1,3-dioxan-5-yl ester, polymer with 1-(1,1-dimethylethoxy)-4-ethenylbenzene and 4-ethenylphenol (9CI) (CA INDEX NAME)

CM 1

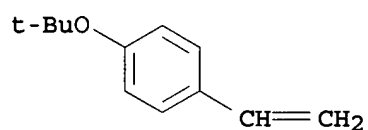
CRN 321660-47-3
 CMF C8 H10 O5



CM 2

CRN 95418-58-9

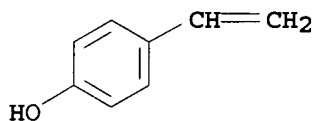
CMF C12 H16 O



CM 3

CRN 2628-17-3

CMF C8 H8 O



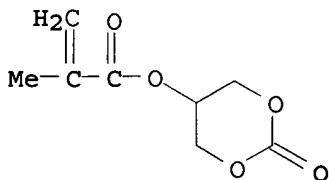
RN 321660-50-8 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-methyltricyclo[3.3.1.1^{3,7}]dec-2-yl ester, polymer with 2-oxo-1,3-dioxan-5-yl 2-methyl-2-propenoate and tetrahydro-5-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

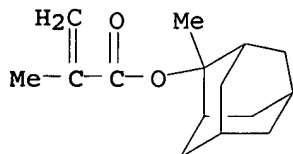
CRN 321660-47-3

CMF C8 H10 O5



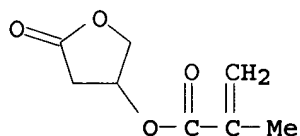
CM 2

CRN 177080-67-0
CMF C15 H22 O2



CM 3

CRN 130224-95-2
CMF C8 H10 O4



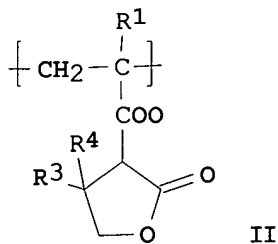
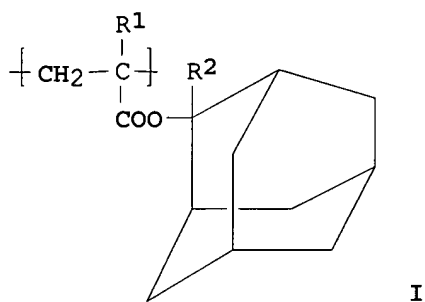
IC ICM G03F007-039
ICS C08F220-26; H01L021-027
CC 74-5 (Radiation Chemistry, Photochemistry, and
Photographic and Other Reprographic Processes)
Section cross-reference(s): 38
ST chem amplification resist **lithog**; acrylic polymer acid
anhydride group resist; dioxanone group acrylic polymer resist
IT Electron beam **lithography**
Resists
(chemical amplification resist composition for **lithog**.)
IT 321660-46-2P **321660-48-4P** 321660-49-5P
321660-50-8P
(chemical amplification resist **composition** for **lithog**
.)
IT 66003-78-9, Triphenylsulfonium triflate
(chemical amplification resist composition for **lithog**.)

L53 ANSWER 9 OF 20 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 2000:823000 HCAPLUS
DOCUMENT NUMBER: 133:367848
TITLE: Positive-working resist composition
INVENTOR(S): Sato, Kenichiro; Kodama, Kunihiro; Aogo,
Toshiaki
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 32 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 5
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
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----- JP 2000321771	A2	20001124	JP 1999-127296	1999 0507
US 6596458	B1	20030722	US 2000-563436	2000 0503
TW 546548	B	20030811	TW 2000-89108532	2000 0504
PRIORITY APPLN. INFO.:			JP 1999-127296	A 1999 0507
			JP 1999-186607	A 1999 0630
			JP 1999-193601	A 1999 0707
			JP 1999-193602	A 1999 0707
			JP 1999-193603	A 1999 0707

GI



AB The title resist composition contains (a) a resin which has repeating units I, II, and ≥ 1 selected from $\text{CH}_2\text{CR}_1(\text{CO}_2\text{H})$,

CH2CR1[XOCR5R7CR6R8O(CR9R10CR11R12O)mR], CH2CR1(ZR13AR14), and CH2CR1(CO2R15SO2OR16) [R1 = H, Me; R2 = C1-4 alkyl; R3, R4 = H, C1-4 alkyl; R5-12 = H, (substituted) alkyl; R = H, (substituted) alkyl, (substituted) cycloalkyl, (substituted) aryl, (substituted) aralkyl; m = 1-10; X = single bond, (substituted) alkylene, (substituted) cycloalkylene, (substituted) arylene, divalent group which is composed of ≥ 1 group selected from ether, thioether, carbonyl, ester, amide, sulfonamide, urethane, and urea groups and is not decomposed by the action of acid; Z = single bond, ether, ester, amide, alkylene, divalent group composed of these groups; R13 = single bond, alkylene, arylene, divalent group composed of these groups; R14 = (substituted) alkyl, (substituted) cycloalkyl, (substituted) aryl, (substituted) aralkyl; R15 = alkylene, arylene, divalent group composed of these groups; R16 = H, (substituted) alkyl, (substituted) cycloalkyl, (substituted) alkenyl, (substituted) aryl, (substituted) aralkyl; A = CONHSO2, SO2NHCO, NHCONHSO2, SO2NHCONH, OCONHSO2, SO2NHCO2, SO2NHSO2] and of which the dissoln. rate to alkaline developing solns. is increased by the action of acid and (b) a compound that generates an acid by irradiation with actinic ray or radiation. The composition shows improved applicability to micro-photo-fabrication using far UV rays, especially ArF excimer laser beams and developability and provides resist patterns with good profile and high resolution contact holes.

IT 307976-36-9P

(pos. photoresist **composition** containing acrylic polymer and acid generator)

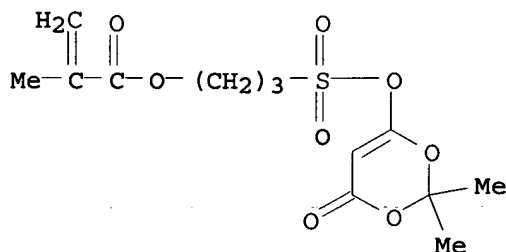
RN 307976-36-9 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 3-[[[(2,2-dimethyl-4-oxo-4H-1,3-dioxin-6-yl)oxy]sulfonyl]propyl ester, polymer with 2-ethyltricyclo[3.3.1.1^{3,7}]dec-2-yl 2-methyl-2-propenoate and tetrahydro-2-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 307976-35-8

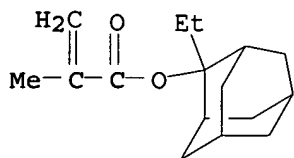
CMF C13 H18 O8 S



CM 2

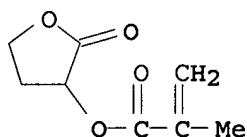
CRN 209982-56-9

CMF C16 H24 O2



CM 3

CRN 195000-66-9
CMF C8 H10 O4



IC ICM G03F007-039
ICS C08F220-04; C08F220-18; C08F220-28; C08K005-00; C08L033-02;
C08L033-04; G03F007-004; H01L021-027
CC 74-5 (Radiation Chemistry, Photochemistry, and
Photographic and Other Reprographic Processes)
Section cross-reference(s): 38
IT 288303-52-6P, Butyrolactone methacrylate-methacrylic
acid-2-methyl-2-adamantyl methacrylate copolymer 307976-24-5P
307976-25-6P 307976-26-7P 307976-27-8P 307976-28-9P
307976-29-0P 307976-30-3P 307976-32-5P 307976-33-6P
307976-34-7P **307976-36-9P** 307976-37-0P 307976-39-2P
(pos. photoresist **composition** containing acrylic polymer and
acid generator)

L53 ANSWER 10 OF 20 HCAPLUS COPYRIGHT 2006 ACS on STN

ACCESSION NUMBER: 2000:619466 HCAPLUS

DOCUMENT NUMBER: 133:230376

TITLE: Monomer for crosslinking agent used in far
UV-sensitive negative-working photoresist
production, photoresist composition using
same, and method for pattern formation for
semiconductor device fabrication using same
INVENTOR(S): Kong, Geun Kyn; Chung, Jae Chang; Kim, Myung
Soo; Kim, Hyung Ki; Kim, Hyung soo; Paek, Ki
Ho

PATENT ASSIGNEE(S): Hyundai Electronics Industries Co., Ltd., S.
Korea

SOURCE: Jpn. Kokai Tokkyo Koho, 19 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

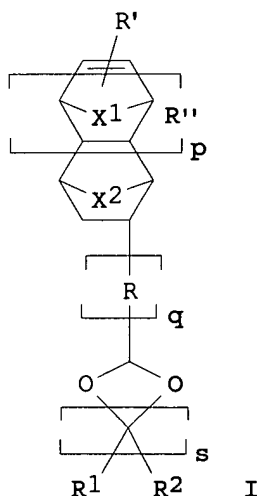
FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
-----	----	-----	-----	-----

JP 2000239436	A2	20000905	JP 2000-43101	2000 0221
KR 2000056467	A	20000915	KR 1999-5807	1999 0222
TW 491875	B	20020621	TW 2000-89101780	2000 0202
US 6312868	B1	20011106	US 2000-501096	2000 0209
US 2002019560	A1	20020214	US 2001-954680	2001 0911
US 6399792	B2	20020604	KR 1999-5807	A 1999 0222
PRIORITY APPLN. INFO.:			US 2000-501096	A3 2000 0209

GI



AB The invention relates to a crosslinking agent for photoresist composition, wherein the crosslinking agent has structure I (X1-2 = CH₂, CH₂CH₂, O, S; p, s = 0-5 integer; q = 0,1; R', R'' = H, methyl; R = C1-10 alkyl, ether, ester, ketone, etc.; R1-2 = C1-10 alkyl, ester, ketone, etc.). The crosslinking agent provides a resist of the high sensitivity.

IT **291519-62-5P**

(crosslinking agent in photoresist composition)

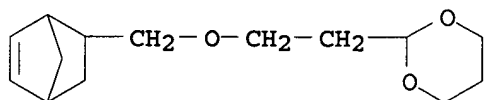
RN 291519-62-5 HCAPLUS

CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, polymer with 2-[2-(bicyclo[2.2.1]hept-5-en-2-ylmethoxy)ethyl]-1,3-dioxane and 2,5-furandione (9CI) (CA INDEX NAME)

CM 1

CRN 291519-60-3

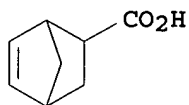
CMF C14 H22 O3



CM 2

CRN 120-74-1

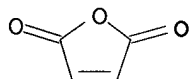
CMF C8 H10 O2



CM 3

CRN 108-31-6

CMF C4 H2 O3



IC ICM C08K005-156
 ICS C08F032-08; C08L101-00; G03F007-038; G03F007-30; G03F007-32
 CC 74-5 (Radiation Chemistry, Photochemistry, and
Photographic and Other Reprographic Processes)
 Section cross-reference(s): 35, 76
 IT 291519-61-4P **291519-62-5P**
 (crosslinking agent in photoresist **composition**)

L53 ANSWER 11 OF 20 HCAPLUS COPYRIGHT 2006 ACS on STN

ACCESSION NUMBER: 2000:274595 HCAPLUS

DOCUMENT NUMBER: 132:315851

TITLE: Photosensitive polymer compositions with high
 dry etching resistance and pattern formation
 using them

INVENTOR(S): Gokochi, Toru; Shinoda, Naomi; Asakawa, Koji;
 Okino, Takeshi

PATENT ASSIGNEE(S): Toshiba Corp., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 28 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 2

PATENT INFORMATION:

PATENT NO. -----	KIND ----	DATE -----	APPLICATION NO. -----	DATE
JP 2000122294	A2	20000428	JP 1999-70591	1999 0316
JP 3763693	B2	20060405		
JP 2001188351	A2	20010710	JP 2000-351365	1999 0316
US 2002098441	A1	20020725	US 2001-884977	2001 0621
US 6541597	B2	20030401		
US 2003149225	A1	20030807	US 2002-246619	2002 0919
US 6660450	B2	20031209		
US 2004043324	A1	20040304	US 2003-635571	2003 0807
US 6824957	B2	20041130		
JP 2004285077	A2	20041014	JP 2004-163529	2004 0601
JP 2004331981	A2	20041125	JP 2004-163504	2004 0601
US 2005031990	A1	20050210	US 2004-937577	2004 0910
US 2005031991	A1	20050210	US 2004-937853	2004 0910
US 2005037283	A1	20050217	US 2004-937313	2004 0910
US 2005037284	A1	20050217	US 2004-937357	2004 0910
US 7029823	B2	20060418		
US 2005048400	A1	20050303	US 2004-937832	2004 0910
PRIORITY APPLN. INFO.:			JP 1998-225747	A 1998 0810
			JP 1998-269320	A 1998 0924
			JP 1999-70591	A3 1999 0316
			JP 2000-351365	A3 1999

0316

US 1999-401181 A3
1999
0923

US 2001-884977 A3
2001
0621

US 2002-246619 A1
2002
0919

US 2003-635571 A1
2003
0807

AB The compns. contain (A) acid generators and (B) polymers containing ≥ 2 5-, 6-, or 7-membered-based bridged alicyclic structures having ≥ 1 C bonded to O via double bonds. Patterns are obtained by forming films of the compns., exposing with chemical radiation, heating, and developing with alkali aqueous solns. This method is useful for manufacture of semiconductor devices. The compns. show high transparency for short-wavelength light and give patterns with high resolution and good adhesion by alkali development.

IT 265999-30-2P

(dry etching-resistant photosensitive compns. containing bridged alicyclic polymers for pattern formation)

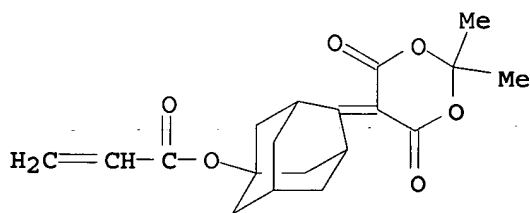
RN 265999-30-2 HCAPLUS

CN 2-Propenoic acid, 4-(2,2-dimethyl-4,6-dioxo-1,3-dioxan-5-ylidene)tricyclo[3.3.1.1^{3,7}]dec-1-yl ester, polymer with tetrahydro-2H-pyran-2-yl 2-methyl-2-propenoate (1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 265999-28-8

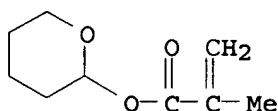
CMF C19 H22 O6



CM 2

CRN 52858-59-0

CMF C9 H14 O3



IC ICM G03F007-039
ICS G03F007-032; H01L021-027
CC 74-5 (Radiation Chemistry, Photochemistry, and
Photographic and Other Reprographic Processes)
Section cross-reference(s): 38, 76
IT 265999-29-9P 265999-30-2P 265999-31-3P 265999-36-8P
265999-37-9P
(dry etching-resistant photosensitive **compns.** containing
bridged alicyclic polymers for pattern formation)

L53 ANSWER 12 OF 20 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 1998:427845 HCAPLUS
DOCUMENT NUMBER: 129:154687
TITLE: Transparent resins, photosensitive
compositions thereof, and pattern formation
using the same, with excellent transparency to
long-wavelength light, dry etching resistance,
and high contrast and resolution
INVENTOR(S): Gokochi, Toru; Asakawa, Koji; Okino, Takeshi;
Shinoda, Naomi; Nakase, Atsushi; Hayase,
Rumiko; Kawamonzen, Yoshihiro
PATENT ASSIGNEE(S): Toshiba Corp., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 33 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 10171120	A2	19980626	JP 1997-272534	1997 1006
JP 3667956	B2	20050706		
US 6071670	A	20000606	US 1997-948425	1997 1010
PRIORITY APPLN. INFO.:			JP 1996-269758	A 1996 1011

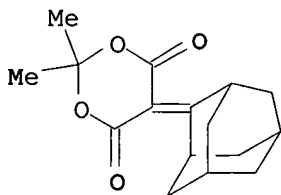
AB The title compns. contain oligomers undergoing main chain degradation
or hydrolysis by an acid and having alicyclic and/or conjugated
polynuclear condensed aromatic structure in the main chain, and
photosensitive acid generator.
IT 210712-17-7P, Deoxycholic acid-5-(2-adamantylidene)-2,2-
dimethyl-1,3-dioxane-4,6-dione copolymer
(transparent resins, photosensitive **compns.** thereof,
and pattern formation using the same, with excellent
transparency to long-wavelength light, dry etching resistance,
and high contrast and resolution)

RN 210712-17-7 HCAPLUS
 CN Cholan-24-oic acid, 3,12-dihydroxy-, (3 α ,5 β ,12 α)-
 , polymer with 2,2-dimethyl-5-tricyclo[3.3.1.1^{3,7}]decylidene-1,3-
 dioxane-4,6-dione (9CI) (CA INDEX NAME)

CM 1

CRN 51757-47-2

CMF C16 H20 O4

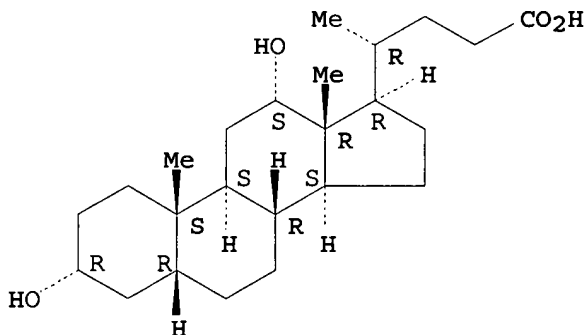


CM 2

CRN 83-44-3

CMF C24 H40 O4

Absolute stereochemistry.



IC ICM G03F007-038

ICS C08G018-34; C08G063-12; C08G069-26; C08L067-00; C08L077-06;
 G03F007-039; H01L021-027

CC 74-5 (Radiation Chemistry, Photochemistry, and
Photographic and Other Reprographic Processes)

IT 541-16-2DP, tert-Butyl malonate, reaction products with
 dibromoadamantane, polymers 702-98-7DP, 2-Methyl-2-adamantanol,
 cotrimers with adamantanedicarbonyl chloride 828-51-3DP,
 1-Adamantanecarboxylic acid, codimer with adamnatanecarbonyl
 chloride 876-53-9DP, 1,3-Dibromoadamantane, reaction products
 with tert-Bu malonate, polymers 2094-72-6DP,
 1-Adamantanecarbonyl chloride, codimer with adamnatanecarboxylic
 acid 2094-72-6DP, 1-Adamantanecarbonyl chloride, cotrimers with
 adamantanedicarbonyl chloride 4405-13-4P, Glyoxal trimer
 dihydrate 115349-14-9P 181017-30-1P, Menthyl
 methacrylate-tert-butyl methacrylate-methacrylic acid copolymer
 210712-16-6P, trans-3,6-Endomethylene-1,2,3,6-tetrahydrophthaloyl
 chloride-(+)-cis-p-menthane-3,8-diol copolymer

210712-17-7P, Deoxycholic acid-5-(2-adamantylidene)-2,2-dimethyl-1,3-dioxane-4,6-dione copolymer 210712-18-8P
 210712-19-9P 210712-20-2P 210712-21-3P 210712-22-4P
 210712-23-5P 210712-24-6P, 4,4'-Diaminodicyclohexylmethane-1,2,3,4-cyclopentanetetracarboxylic dianhydride copolymer
 210712-25-7P 210754-99-7P 210755-03-6P 210776-45-7DP,
 cotrimers with methyladamantanol 210776-46-8P 210776-47-9P,
 Adamantanedicarbonyl chloride-naphthalenedicarbonyl
 chloride-deoxycholic acid copolymer 210776-48-0P 210776-51-5P
 210776-52-6P 210776-53-7P 210776-56-0P 210776-59-3P
 210776-61-7P

(transparent resins, photosensitive compns. thereof,
 and pattern formation using the same, with excellent
 transparency to long-wavelength light, dry etching resistance,
 and high contrast and resolution)

L53 ANSWER 13 OF 20 HCAPLUS COPYRIGHT 2006 ACS on STN

ACCESSION NUMBER: 1996:302911 HCAPLUS
 DOCUMENT NUMBER: 125:45126
 TITLE: Photosensitive resin composition
 INVENTOR(S): Gybin, Alexander S.; Van Iseghem, Lawrence C.
 PATENT ASSIGNEE(S): Chromaline Corp., USA
 SOURCE: U.S., 11 pp., Division of U. S. Ser. No. 28,
 420.
 CODEN: USXXAM
 DOCUMENT TYPE: Patent
 LANGUAGE: English
 FAMILY ACC. NUM. COUNT: 2
 PATENT INFORMATION:

PATENT NO. -----	KIND ----	DATE -----	APPLICATION NO. -----	DATE
US 5506089	A	19960409	US 1994-195258	1994 0214
US 6020436	A	20000201	US 1993-28420	1993 0309
PRIORITY APPLN. INFO.:			US 1993-28420	A3 1993 0309

GI For diagram(s), see printed CA Issue.

AB A universal method to make photosensitive polymers from poly(vinyl alc.) and poly(vinyl pyridine) is disclosed which generally does not require final purification and can produce photosensitive polymers which are of similar photosensitivity whether prepared with a poly(vinyl alc.) or poly(vinyl pyridine) backbone. These polymers comprise a heterocyclic, light-sensitive pendant group including a moiety having the formula I or II wherein Z1 denotes the atoms necessary to form a substituted or unsubstituted aromatic heterocyclic ring; Z2 denotes the atoms necessary to form a substituted or unsubstituted aromatic or aromatic heterocyclic ring; R is hydrogen or a substituted or unsubstituted alkyl group; Y is a residue from a grafting group that is capable of grafting the pendant group onto a polymeric backbone; n is 1 or 2.

IT 178058-96-3P 178058-97-4P 178058-99-6P
 (preparation and use in photosensitive compns.)

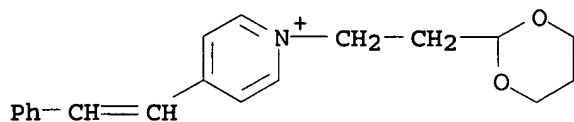
RN 178058-96-3 HCAPLUS

CN Pyridinium, 1-[2-(1,3-dioxan-2-yl)ethyl]-4-(2-phenylethenyl)-, bromide, polymer with ethenyl acetate (9CI) (CA INDEX NAME)

CM 1

CRN 178058-92-9

CMF C19 H22 N O2 . Br



● Br⁻

CM 2

CRN 108-05-4

CMF C4 H6 O2



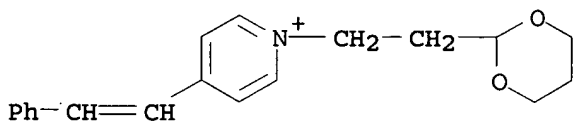
RN 178058-97-4 HCAPLUS

CN Pyridinium, 1-[2-(1,3-dioxan-2-yl)ethyl]-4-(2-phenylethenyl)-, bromide, polymer with ethenol (9CI) (CA INDEX NAME)

CM 1

CRN 178058-92-9

CMF C19 H22 N O2 . Br

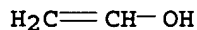


● Br⁻

CM 2

CRN 557-75-5

CMF C2 H4 O

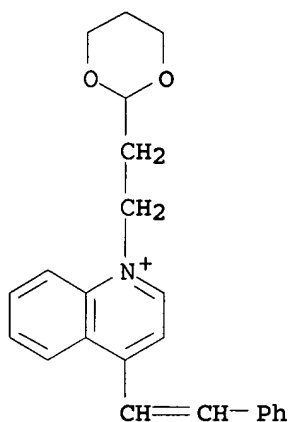


RN 178058-99-6 HCAPLUS
 CN Quinolinium, 1-[2-(1,3-dioxan-2-yl)ethyl]-4-(2-phenylethenyl)-, bromide, polymer with ethenyl acetate (9CI) (CA INDEX NAME)

CM 1

CRN 178058-98-5

CMF C23 H24 N O2 . Br



● Br⁻

CM 2

CRN 108-05-4

CMF C4 H6 O2

AcO-CH=CH₂

IC ICM G03C001-73

INCL 430287000

CC 74-5 (Radiation Chemistry, Photochemistry, and
Photographic and Other Reprographic Processes)

IT 178058-96-3P 178058-97-4P 178058-99-6P

178059-02-4P

(preparation and use in photosensitive **compns.**)

L53 ANSWER 14 OF 20 HCAPLUS COPYRIGHT 2006 ACS on STN

ACCESSION NUMBER: 1995:929522 HCAPLUS

DOCUMENT NUMBER: 124:71648

TITLE: Image-forming material and method

INVENTOR(S): Hirayama, Shigeru; Watanabe, Jiro; Tsurukawa, Naoichi

PATENT ASSIGNEE(S): Toppan Printing Co Ltd, Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 6 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 07199460	A2	19950804	JP 1993-352238	1993 1227
JP 2956463	B2	19991004	JP 1993-352238	1993 1227

PRIORITY APPLN. INFO.:
 1993
 1227

AB The title material comprises a photosensitive layer containing a photopolymerizable compound and a photopolymn. initiator, and a colored layer containing a dye or pigment and a nonphotopolymerizable organic polymer binder. High quality simple proofs can be produced easily by using the material on printing paper.

IT 172084-40-1

(photoimaging **composition** useful for manufacture of proofs)

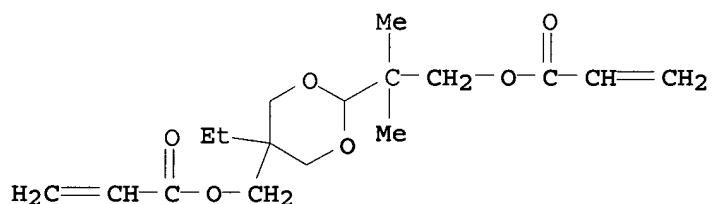
RN 172084-40-1 HCAPLUS

CN 2-Propenoic acid, [2-[1,1-dimethyl-2-[(1-oxo-2-propenyl)oxy]ethyl]-5-ethyl-1,3-dioxan-5-yl]methyl ester, polymer with Aronix M 7100 (9CI) (CA INDEX NAME)

CM 1

CRN 87320-05-6

CMF C17 H26 O6



CM 2

CRN 76723-57-4

CMF Unspecified

CCI MAN

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

IC ICM G03F007-004

ICS G03F007-004; G03F003-10; G03F007-027; G03F007-031; G03F007-105; G03F007-34

CC 74-6 (Radiation Chemistry, Photochemistry, and **Photographic** and Other Reprographic Processes)

IT 137335-87-6 172084-40-1

(photoimaging **composition** useful for manufacture of proofs)

L53 ANSWER 15 OF 20 HCAPLUS COPYRIGHT 2006 ACS on STN
 ACCESSION NUMBER: 1992:642751 HCAPLUS

DOCUMENT NUMBER: 117:242751
 TITLE: Photosensitive materials using silver halide development-induced polymerization
 INVENTOR(S): Hirai, Hiroyuki
 PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 24 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO. -----	KIND ----	DATE -----	APPLICATION NO. -----	DATE
JP 04147263	A2	19920520	JP 1990-272878	1990 1011
JP 2592718	B2	19970319		
US 5192639	A	19930309	US 1991-774483	1991 1010
PRIORITY APPLN. INFO.:			JP 1990-272878	A 1990 1011

AB A photosensitive layer of the title materials is made up of microcapsules containing Ag halides, reducing agents, polymerizable compds., color image-forming substances, and bases or their precursors on a support. The photosensitive materials contain an oxide or its salt of ≥ 1 element selected from Cr, Mo, and W with 6 valences in the layer. The materials produce clear images at a relatively low temperature and in a short time. Thus, a support was coated with a dispersion of microcapsules containing the above constituents and K₂CrO₄ to give a photosensitive sheet.

IT 116321-27-8
 (photoimaging polymerization-type composition containing, with silver halide)

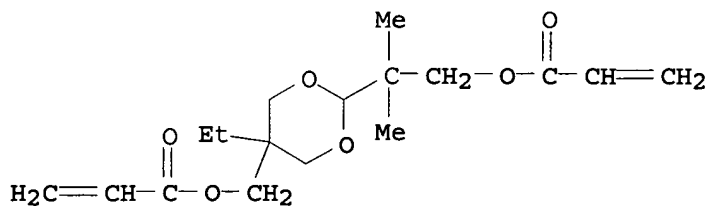
RN 116321-27-8 HCAPLUS

CN 2-Propenoic acid, [2-[1,1-dimethyl-2-[(1-oxo-2-propenyl)oxy]ethyl]-5-ethyl-1,3-dioxan-5-yl]methyl ester, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 87320-05-6

CMF C17 H26 O6



IC ICM G03F007-004
 ICS G03F007-06

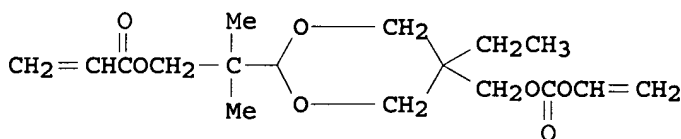
CC 74-4 (Radiation Chemistry, Photochemistry, and
Photographic and Other Reprographic Processes)
 IT 71512-49-7 90216-38-9 116321-27-8 136168-28-0
 (photoimaging polymerization-type **composition** containing, with silver
 halide)

L53 ANSWER 16 OF 20 HCAPLUS COPYRIGHT 2006 ACS on STN

ACCESSION NUMBER: 1990:641566 HCAPLUS
 DOCUMENT NUMBER: 113:241566
 TITLE: Optical recording material
 INVENTOR(S): Tachibana, Shinichi
 PATENT ASSIGNEE(S): Canon K. K., Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 8 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
-----	----	-----	-----	
JP 02078034	A2	19900319	JP 1988-228476	1988 0914
PRIORITY APPLN. INFO.:			JP 1988-228476	1988 0914

GI



AB An optical recording material, which is a hardened resin layer
 provided with preformat signals and tracking grooves coated on a
 transparent disk, is obtained by using a UV-hardenable resin
 composition containing as a prepolymer component a carbonate diol diarylate
 (average mol. weight 500-5000), I (as an acrylate component), and a
 photopolymer. initiator.

IT 130725-09-6 130726-44-2 130726-45-3
 130743-50-9

(UV-curable **comps.** containing, for optical recording
 material preparation)

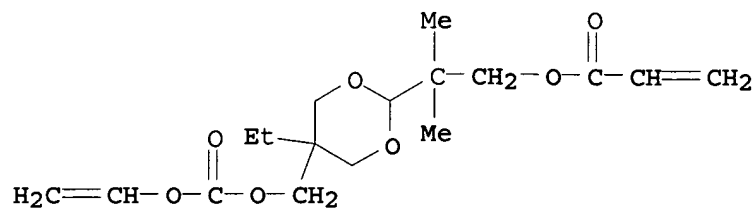
RN 130725-09-6 HCAPLUS

CN 2-Propenoic acid, 2-[5-[[[(ethenyloxy)carbonyl]oxy]methyl]-5-ethyl-
 1,3-dioxan-2-yl]-2-methylpropyl ester, polymer with DN 983
 2-propenoate and 2-[3a,4,5,6,7,7a-hexahydro-4,7-methano-1H-inden-
 5(or 6)-yl]ethyl 2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 130725-07-4

CMF C17 H26 O7

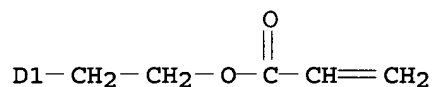
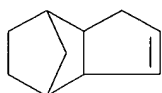


CM 2

CRN 83784-39-8

CMF C15 H20 O2

CCI IDS



CM 3

CRN 130589-17-2

CMF C3 H4 O2 . x Unspecified

CM 4

CRN 130939-35-4

CMF	Unspecified
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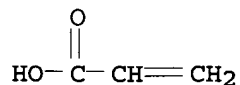
CCI MAN

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

CM 5

CRN 79-10-7

CMF C3 H4 O2

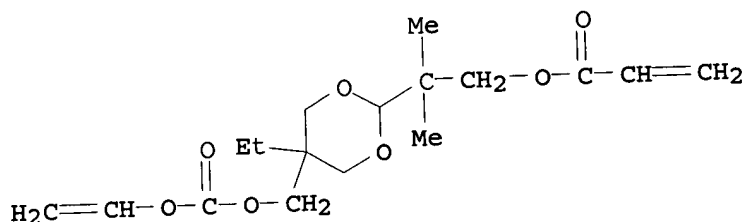


RN 130726-44-2 HCAPLUS

CN 2-Propenoic acid, 2-[5-[[[(ethenyloxy)carbonyl]oxy]methyl]-5-ethyl-1,3-dioxan-2-yl]-2-methylpropyl ester, polymer with Nippollan 983
2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 130725-07-4
CMF C17 H26 O7



CM 2

CRN 130589-17-2
CMF C3 H4 O2 . x Unspecified

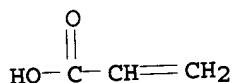
CM 3

CRN 130939-35-4
CMF Unspecified
CCI MAN

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

CM 4

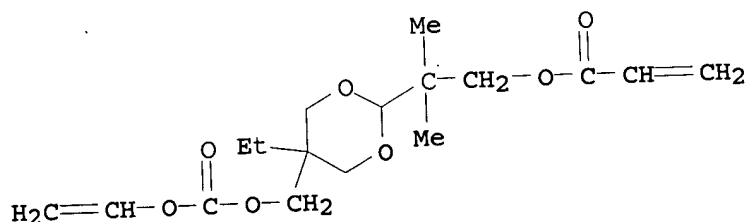
CRN 79-10-7
CMF C3 H4 O2



RN 130726-45-3 HCAPLUS
CN 2-Propenoic acid, 2-[5-[[[(ethenyloxy)carbonyl]oxy]methyl]-5-ethyl-1,3-dioxan-2-yl]-2-methylpropyl ester, polymer with Nippollan 982
2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 130725-07-4
CMF C17 H26 O7



CM 2

CRN 130589-16-1
 CMF C3 H4 O2 . x Unspecified

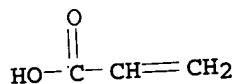
CM 3

CRN 115803-95-7
 CMF Unspecified
 CCI PMS, MAN

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

CM 4

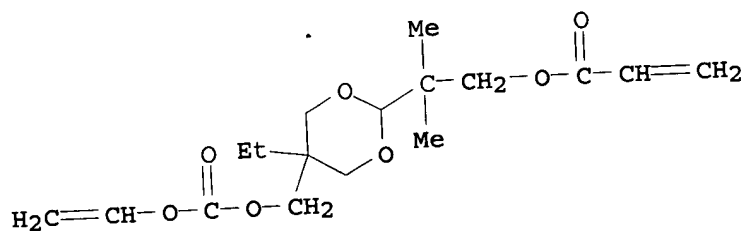
CRN 79-10-7
 CMF C3 H4 O2



RN 130743-50-9 HCAPLUS
 CN 2-Propenoic acid, 2-[5-[[[(ethenyloxy)carbonyl]oxy]methyl]-5-ethyl-1,3-dioxan-2-yl]-2-methylpropyl ester, polymer with 2-[3a,4,5,6,7,7a-hexahydro-4,7-methano-1H-inden-5(or 6)-yl]ethyl 2-propenoate and Nippollan 982 propenoate (9CI) (CA INDEX NAME)

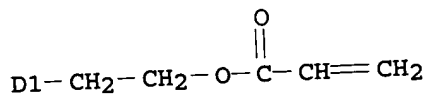
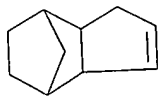
CM 1

CRN 130725-07-4
 CMF C17 H26 O7



CM 2

CRN 83784-39-8
 CMF C15 H20 O2
 CCI IDS



CM 3

CRN 130589-16-1
CMF C3 H4 O2 . x Unspecified

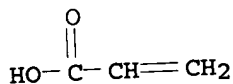
CM 4

CRN 115803-95-7
CMF Unspecified
CCI PMS, MAN

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

CM 5

CRN 79-10-7
CMF C3 H4 O2

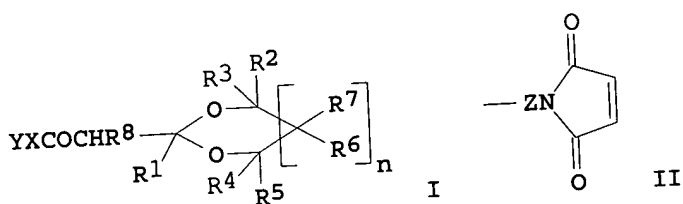


IC ICM G11B007-24
ICS C08F002-48
ICA B32B027-30; C08J007-04
CC 74-12 (Radiation Chemistry, Photochemistry, and
Photographic and Other Reprographic Processes)
IT 130725-09-6 130726-44-2 130726-45-3
130743-50-9
(UV-curable compns. containing, for optical recording
material preparation)

L53 ANSWER 17 OF 20 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 1990:506442 HCAPLUS
DOCUMENT NUMBER: 113:106442
TITLE: Unsaturated β -keto ester acetals and
their use in photoimaging compositions
Schulthess, Adrian; Hunziker, Max
Ciba-Geigy A.-G., Switz.
Eur. Pat. Appl., 34 pp.
INVENTOR(S):
PATENT ASSIGNEE(S):
SOURCE: CODEN: EPXXDW
DOCUMENT TYPE: Patent
LANGUAGE: German
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
EP 347381	A1	19891220	EP 1989-810430	1989 0607
EP 347381 R: BE, CH, DE, ES, FR, GB, IT, LI, NL, SE US 5059698	B1 A	19920212 19911022	US 1989-363801	1989 0609
CA 1337771	A1	19951219	CA 1989-602272	1989 0609
JP 02051509	A2	19900221	JP 1989-150333	1989 0613
PRIORITY APPLN. INFO.:			CH 1988-2257	A 1988 0613

OTHER SOURCE(S): MARPAT 113:106442
GI



AB The title compds. I or YXCOCHR8CR10R12OR13 [n = 0-2; R1 = H, alkyl, Ph, benzyl, etc.; R2-R8 = H, halogen, alkyl, Ph, naphthyl, CO2R9, -p-C6H4CO2R9, SO2R9 (R9 = alkyl, Ph); X = O, S, NR10 (R10 = H, R9); Y = CR11:CH2, -p-C6H4-CR11:CH2, ZO2CCH:CHCO2R11, ZO2CCH:CHCO2R11, ZNR11CO2R11:CH2, ZO2CCH:CHCO2R11, ZNR11CH2COCH:CHCO2R11 (R11 = R10; Z = ≥2 methylene group-containing residue; R12, R13 = R9, naphthyl)] are prepared for use in photoimaging compns. for photoresists, integrated circuit manufacturing, printing plates, and the like.

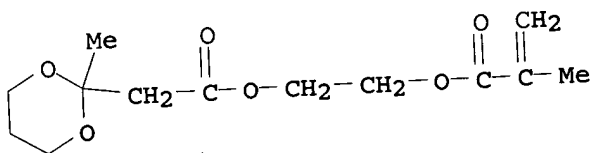
IT 128692-56-8P 128692-58-0P
(preparation of, for photoimaging compns.)

RN 128692-56-8 HCAPLUS
CN 1,3-Dioxane-2-acetic acid, 2-methyl-, 2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl ester, polymer with [(2-methyl-1-oxo-2-propenyl)oxy]methyl 3-oxobutanoate (9CI) (CA INDEX NAME)

CM 1

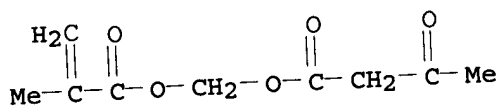
CRN 128692-57-9
CMF C13 H20 O6

WALKE 10/800,133



CM 2

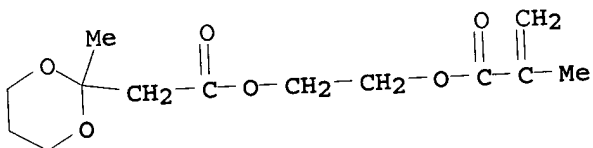
CRN 122458-42-8
CMF C9 H12 O5



RN 128692-58-0 HCAPLUS
CN 1,3-Dioxane-2-acetic acid, 2-methyl-, 2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl ester, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 128692-57-9
CMF C13 H20 O6



IC ICM C07D317-30
ICS C07D319-06; C07C069-66; C08F020-18; G03F007-10
CC 74-5 (Radiation Chemistry, Photochemistry, and
Photographic and Other Reprographic Processes)
Section cross-reference(s): 28, 76
IT 128692-53-5P 128692-56-8P 128692-58-0P
128692-59-1P 128692-61-5P 128692-63-7P 128692-65-9P
(preparation of, for photoimaging compns.)

L53 ANSWER 18 OF 20 HCAPLUS COPYRIGHT 2006 ACS on STN

ACCESSION NUMBER: 1985:87671 HCAPLUS
DOCUMENT NUMBER: 102:87671
TITLE: Photocrosslinkable compositions
PATENT ASSIGNEE(S): Ricoh Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 10 pp.
CODEN: JKXXAF

DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
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USHA SHRESTHA EIC 1700 REM 4B28

WALKE 10/800,133

JP 59058427

A2

19840404

JP 1982-169203

1982
0928

PRIORITY APPLN. INFO.:

JP 1982-169203

1982
0928

GI

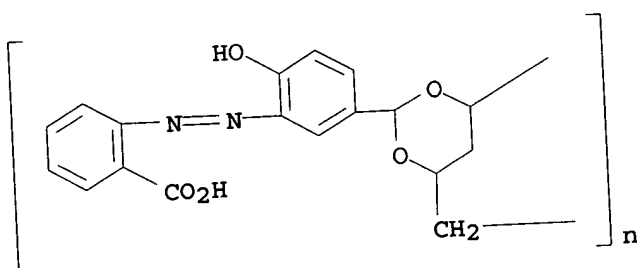
* STRUCTURE DIAGRAM TOO LARGE FOR DISPLAY - AVAILABLE VIA OFFLINE PRINT
*

AB Photocrosslinkable compns. for printing plate preparation contain a Co(III) complex, a photoreducing agent, a H donor, and a chelating macromol. ligand having the repeating unit I (R = H, Me, OH, OMe, OEt; R1 = II, VI, VII, VIII, IX, X; R2, R3 = H, Me, OH, OMe, OEt, CO2H, SO3H, N(Me)2, III, IV, V, NO, NO3, Cl, Br). Thus, a chelating macromol. ligand having the repeating unit XI 100, hexamminecobalt(III) trifluoroacetate 150, 9,10-phenanthrenequinone 30, and polyethylene glycol 50 mg were dissolved in MeCOEt 10 mL, coated on an Al sheet, and dried to give a photosensitive plate useful for making a printing plate.

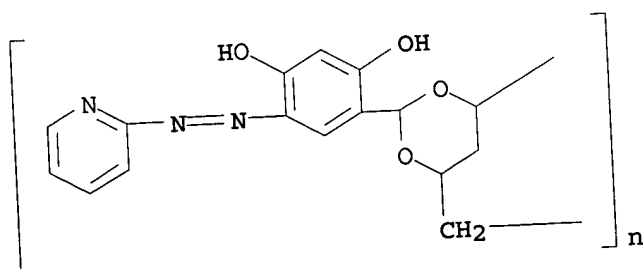
IT 94797-91-8 94797-92-9 94797-93-0
94797-94-1 94797-95-2

(photocrosslinkable compns. containing, for printing plate preparation)

RN 94797-91-8 HCAPLUS
CN Poly[[2-[3-[(2-carboxyphenyl)azo]-4-hydroxyphenyl]-1,3-dioxane-4,6-diyl]methylene] (9CI) (CA INDEX NAME)

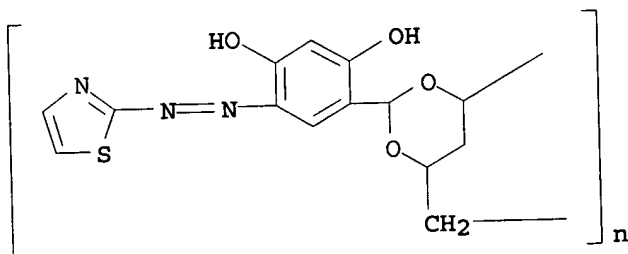


RN 94797-92-9 HCAPLUS
CN Poly[[2-[2,4-dihydroxy-5-(2-pyridinylazo)phenyl]-1,3-dioxane-4,6-diyl]methylene] (9CI) (CA INDEX NAME)

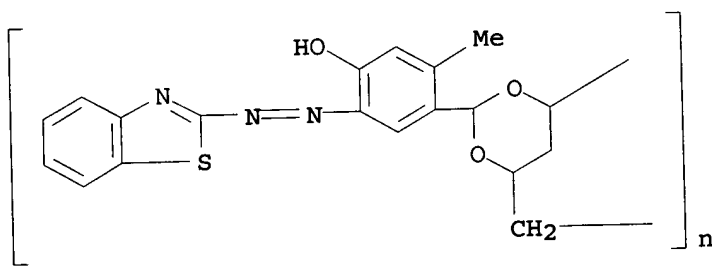


USHA SHRESTHA EIC 1700 REM 4B28

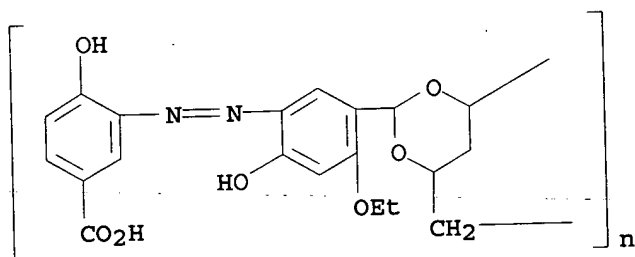
RN 94797-93-0 HCAPLUS
 CN Poly[[2-[2,4-dihydroxy-5-(2-thiazolylazo)phenyl]-1,3-dioxane-4,6-diyl]methylene] (9CI) (CA INDEX NAME)



RN 94797-94-1 HCAPLUS
 CN Poly[[2-[5-(2-benzothiazolylazo)-4-hydroxy-2-methylphenyl]-1,3-dioxane-4,6-diyl]methylene] (9CI) (CA INDEX NAME)



RN 94797-95-2 HCAPLUS
 CN Poly[[2-[5-[(5-carboxy-2-hydroxyphenyl)azo]-2-ethoxy-4-hydroxyphenyl]-1,3-dioxane-4,6-diyl]methylene] (9CI) (CA INDEX NAME)



IC G03C001-71; C08F008-30; C08L029-14
 CC 74-6 (Radiation Chemistry, Photochemistry, and
Photographic and Other Reprographic Processes)
 IT 84-11-7 25322-68-3 59561-55-6 94797-91-8
 94797-92-9 94797-93-0 94797-94-1
 94797-95-2
 (photocrosslinkable **compns.** containing, for printing
 plate preparation)

L53 ANSWER 19 OF 20 HCAPLUS COPYRIGHT 2006 ACS on STN

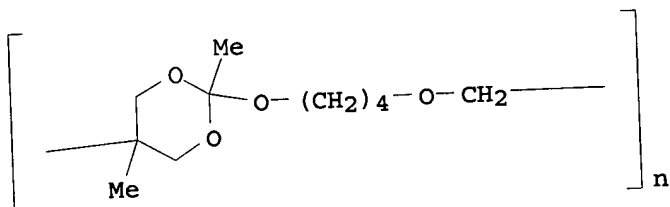
ACCESSION NUMBER: 1981:471073 HCAPLUS
 DOCUMENT NUMBER: 95:71073
 TITLE: Photosensitive mixture for relief images
 INVENTOR(S): Buhr, Gerhard; Ruckert, Hans
 PATENT ASSIGNEE(S): Hoechst A.-G., Fed. Rep. Ger.
 SOURCE: Eur. Pat. Appl., 47 pp.
 CODEN: EPXXDW
 DOCUMENT TYPE: Patent
 LANGUAGE: German
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
EP 22571	A1	19810121	EP 1980-104006	1980 0711
EP 22571 R: AT, BE, CH, DE, FR, GB, IT, NL, SE DE 2928636	B1 A1	19821222 19810212	DE 1979-2928636	1979 0716
CA 1133743	A1	19821019	CA 1980-355539	1980 0704
AU 8060152	A1	19810122	AU 1980-60152	1980 0707
AU 533172 AT 2099	B2 E	19831103 19830115	AT 1980-104006	1980 0711
BR 8004395	A	19810127	BR 1980-4395	1980 0715
ZA 8004267	A	19810729	ZA 1980-4267	1980 0715
US 4311782	A	19820119	US 1980-169133	1980 0715
JP 56017345	A2	19810219	JP 1980-96290	1980 0716
JP 63020325 PRIORITY APPLN. INFO.:	B4	19880427	DE 1979-2928636	A 1979 0716
			EP 1980-104006	A 1980 0711

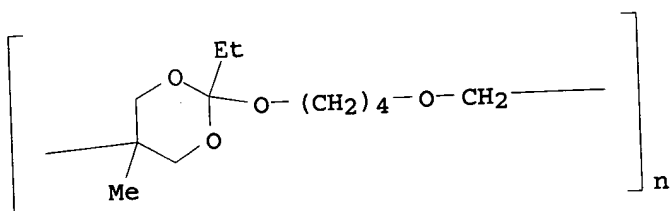
AB Radiation-sensitive pos.-working compns. for the production of relief images are comprised of an acid-forming compound and a polymeric compound with recurring orthocarbonic acid ester groups in the main chain and whose solubility in a liquid developer is increased by the presence of an acid. Thus, a polymeric orthoester was prepared by mixing 1,2,6-hexanetriol 23.65, tri-Me orthoformate 22.5 g, and

p-toluenesulfonic acid 25 mg, distilling off MeOH over 5 h, heating to 160°, adding Et₂O 50 mL, stirring with K₂CO₃, filtering, and removing the solvent under reduced pressure. This polymeric orthoester 1.2, a cresol-HCHO resin 4.0, 2-acenaphth-5-yl-4,6-bis(trichloromethyl)-s-triazine 0.2, and MeCOEt 94.6 parts were mixed, coated on a grained Al plate, exposed with a Leitz Prado projector at 65 cm and developed in an alkaline solution to give a pos. copy of a black-and-white line image capable of being used as an offset printing plate.

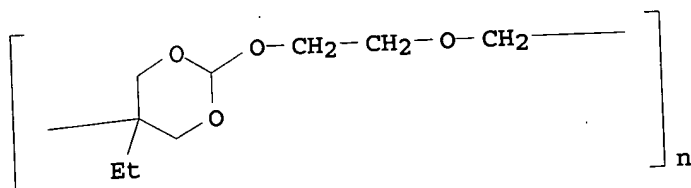
IT 78538-26-8 78538-27-9 78538-28-0
 78538-29-1 78538-30-4 78538-31-5
 78538-32-6 78538-33-7 78538-34-8
 78538-35-9 78538-36-0 78538-37-1
 78538-38-2 78538-39-3 78538-40-6
 (radiation-sensitive resist compns. containing,
 pos.-working)
 RN 78538-26-8 HCAPLUS
 CN Poly[(2,5-dimethyl-1,3-dioxane-5,2-diyl)oxy-1,4-
 butanediylloxymethylene] (9CI) (CA INDEX NAME)



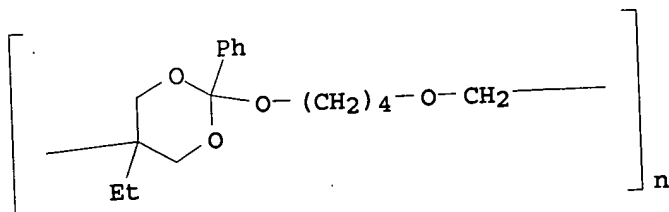
RN 78538-27-9 HCAPLUS
 CN Poly[(2-ethyl-5-methyl-1,3-dioxane-5,2-diyl)oxy-1,4-
 butanediylloxymethylene] (9CI) (CA INDEX NAME)



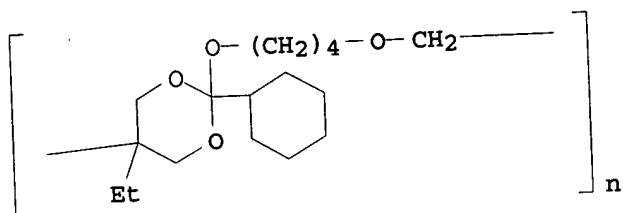
RN 78538-28-0 HCAPLUS
 CN Poly[(5-ethyl-1,3-dioxane-5,2-diyl)oxy-1,2-ethanediylloxymethylene]
 (9CI) (CA INDEX NAME)



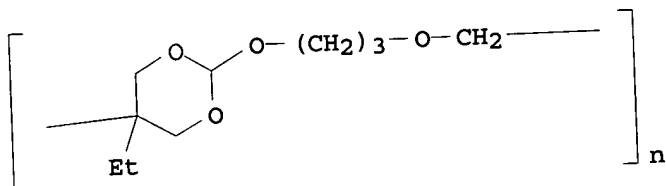
RN 78538-29-1 HCAPLUS
 CN Poly[(5-ethyl-2-phenyl-1,3-dioxane-5,2-diyl)oxy-1,4-
 butanediylloxymethylene] (9CI) (CA INDEX NAME)



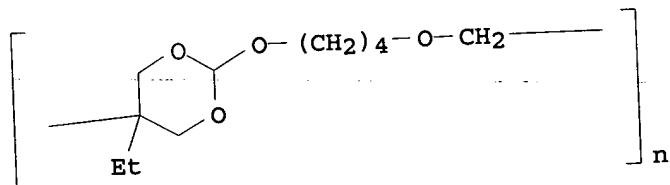
RN 78538-30-4 HCAPLUS
 CN Poly[(2-cyclohexyl-5-ethyl-1,3-dioxane-5,2-diyl)oxy-1,4-butanediloxymethylene] (9CI) (CA INDEX NAME)



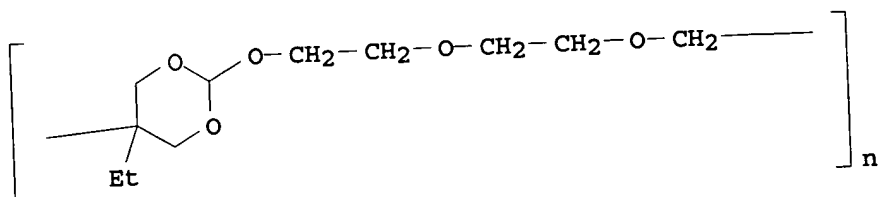
RN 78538-31-5 HCAPLUS
 CN Poly[(5-ethyl-1,3-dioxane-5,2-diyl)oxy-1,3-propanediloxymethylene] (9CI) (CA INDEX NAME)



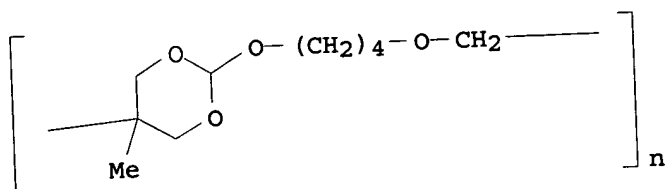
RN 78538-32-6 HCAPLUS
 CN Poly[(5-ethyl-1,3-dioxane-5,2-diyl)oxy-1,4-butanediloxymethylene] (9CI) (CA INDEX NAME)



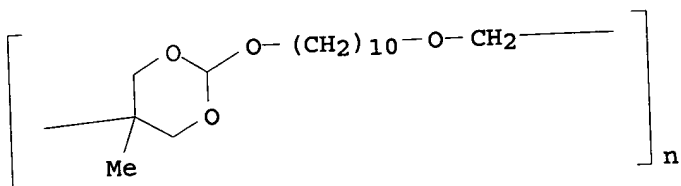
RN 78538-33-7 HCAPLUS
 CN Poly[(5-ethyl-1,3-dioxane-5,2-diyl)oxy-1,2-ethanediloxymethylene] (9CI) (CA INDEX NAME)



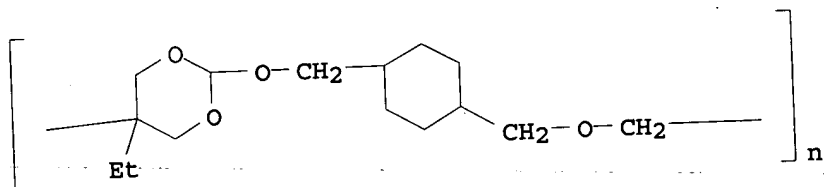
RN 78538-34-8 HCAPLUS
 CN Poly[(5-methyl-1,3-dioxane-5,2-diyl)oxy-1,4-butanediloxymethylene] (9CI) (CA INDEX NAME)



RN 78538-35-9 HCAPLUS
 CN Poly[(5-methyl-1,3-dioxane-5,2-diyl)oxy-1,10-decanediloxymethylene] (9CI) (CA INDEX NAME)

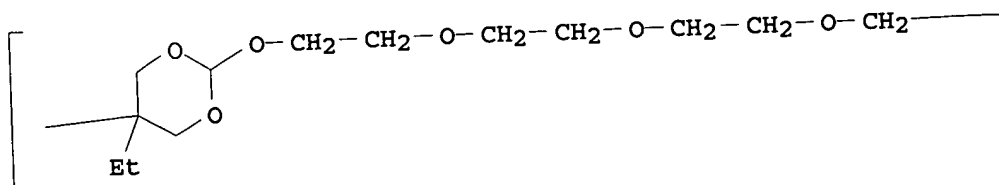


RN 78538-36-0 HCAPLUS
 CN Poly[(5-ethyl-1,3-dioxane-5,2-diyl)oxymethylene-1,4-cyclohexanediylmethylenedioxy] (9CI) (CA INDEX NAME)



RN 78538-37-1 HCAPLUS
 CN Poly[(5-ethyl-1,3-dioxane-5,2-diyl)oxy-1,2-ethanediyoxy-1,2-ethanediloxymethylene] (9CI) (CA INDEX NAME)

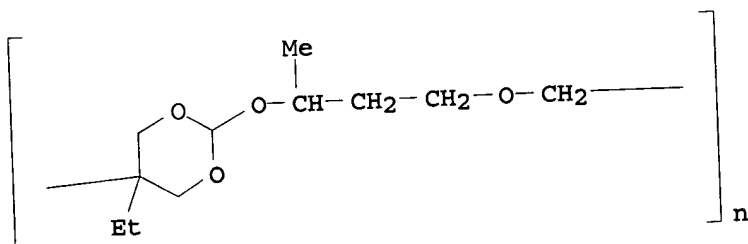
PAGE 1-A



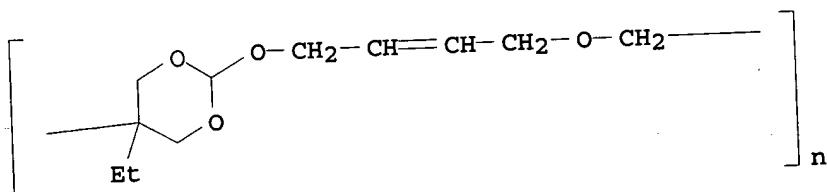
PAGE 1-B



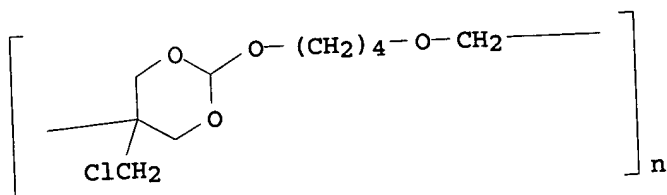
RN 78538-38-2 HCAPLUS
 CN Poly[(5-ethyl-1,3-dioxane-5,2-diyl)oxy(1-methyl-1,3-propanediyl)oxymethylene] (9CI) (CA INDEX NAME)



RN 78538-39-3 HCAPLUS
 CN Poly[(5-ethyl-1,3-dioxane-5,2-diyl)oxy-2-butene-1,4-diylloxymethylene] (9CI) (CA INDEX NAME)



RN 78538-40-6 HCAPLUS
 CN Poly[[5-(chloromethyl)-1,3-dioxane-5,2-diyl]oxy-1,4-butanediylloxymethylene] (9CI) (CA INDEX NAME)



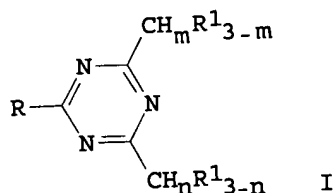
IC G03C001-72
 CC 74-6 (Radiation Chemistry, Photochemistry, and
 Photographic Processes)
 IT Lithographic plates
 Printing plates
 (photosensitive compns. containing polymeric orthoesters for)
 IT 467-63-0 6542-67-2 9016-83-5 36451-09-9 38686-70-3
 41749-18-2 42573-57-9 64524-15-8 69432-40-2 69432-41-3
 69432-57-1 78537-86-7 78538-26-8 78538-27-9
 78538-28-0 78538-29-1 78538-30-4
 78538-31-5 78538-32-6 78538-33-7
 78538-34-8 78538-35-9 78538-36-0
 78538-37-1 78538-38-2 78538-39-3
 78538-40-6
 (radiation-sensitive resist compns. containing,
 pos.-working)

L53 ANSWER 20 OF 20 HCAPLUS COPYRIGHT 2006 ACS on STN
 ACCESSION NUMBER: 1980:485223 HCAPLUS
 DOCUMENT NUMBER: 93:85223
 TITLE: Radiation-sensitive copying composition
 INVENTOR(S): Buhr, Gerhard
 PATENT ASSIGNEE(S): Hoechst A.-G., Fed. Rep. Ger.
 SOURCE: U.S., 9 pp.
 CODEN: USXXAM
 DOCUMENT TYPE: Patent
 LANGUAGE: English
 FAMILY ACC. NUM. COUNT: 2
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 4189323	A	19800219	US 1978-899272	1978 0424
DE 2718259	A1	19781102	DE 1977-2718259	1977 0425
DE 2718259	C2	19821125	DE 1977-2718259	A 1977 0425

PRIORITY APPLN. INFO.:

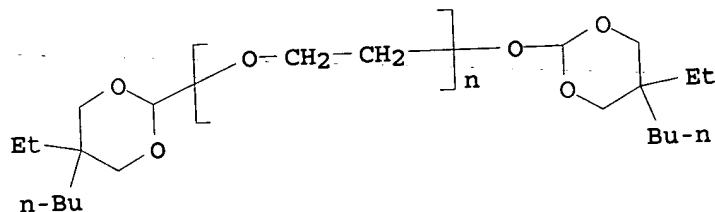
GI



AB Radiation-sensitive copying compns. for use in preparing printing plates, color proofing films, resists, and the like are composed of an ethylenically unsatd. compound capable of undergoing a polymerization reaction initiated by free radicals or a compound capable of undergoing a cationic polymerization under the action of acid catalysts and an s-triazine of formula I (R = a substituted or unsubstituted bi- or polynuclear aromatic or heterocyclic aromatic group which can be partially hydrogenated and is linked by an unsatd. nuclear C atom; R¹ = Br or Cl; m, n = 0-3; and m + n = <5). Thus, an electrolytically roughened and anodized Al plate was whirl-coated with a coating solution containing trimethylolethane triacrylate 6.7, methacrylic acid-Me methacrylate copolymer (acid no 115) 6.5, I (R = 4-ethoxy-1-naphthyl; R¹ = Cl; m, n = 0) 0.12, ethylene glycol monoethyl ether 64.0, BuOAc 22.7, and 2,4-dinitro-6-chloro-2'-acetamido-5'-methoxy-4'-(β-hydroxyethyl-β'-cyanoethyl)aminoazobenzene 0.3 parts by weight to give a 3-4 g/m² dry layer. After providing the plate with a 4 μm thick protective layer of poly(vinyl alc.), the layer was exposed for 30 s at 110 cm to a 5 kW metal halide lamp under a line/screen original, and developed with 1.5% aqueous Na metasilicate to give a neg. of the original that when used in an offset press produced 200,000 copies of good quality.

IT 74217-21-3
(radiation-sensitive compns. containing triazine derivs. and, for photoresists, color proofing films, and printing plates)

RN 74217-21-3 HCAPLUS
CN Poly(oxy-1,2-ethanediyl), α-(5-butyl-5-ethyl-1,3-dioxan-2-yl)-ω-[(5-butyl-5-ethyl-1,3-dioxan-2-yl)oxy]- (9CI) (CA INDEX NAME)



IC G03C001-68

INCL 430281000

CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic Processes)

IT 109-16-0 548-62-9 1484-13-5 1628-58-6 9003-35-4
9016-83-5 19778-85-9 23807-28-5 24687-64-7 25068-38-6
25086-15-1 41137-60-4 58601-54-0 64502-14-3 69418-08-2
69666-21-3 74217-21-3 74217-60-0

(radiation-sensitive **compns.** containing triazine derivs.
and, for photoresists, color proofing films, and printing
plates)

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